



PLATHINIUM
PLASMA THIN FILM INTERNATIONAL UNION MEETING

23-27 September 2019
Antibes, French Riviera

FINAL PROGRAM EXHIBITORS GUIDE



Partners & sponsors

Gold sponsor

HORIBA

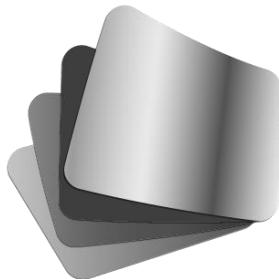


neyco

Vacuum & Materials

The logo for Tecuum features a blue circular icon containing a stylized white letter "T". To the right of the icon, the word "tecuum" is written in a lowercase, bold, blue sans-serif font. Below "tecuum", the words "applied vacuum technology" are written in a smaller, blue, sans-serif font.

tecuum
applied vacuum technology



PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

23 - 27 September 2019
Antibes, French Riviera

www.plathinium.com

© Editions SFV 2019
19 rue du Renard - F-75004 Paris, France

ISBN: 978-2-918641-21-6
Legal Deposit: December 2019

The texts of this volume are the exclusive property of the French Vacuum Society.
Reproduction is prohibited without his consent. The editors assume no responsibility for any errors or omissions that may occur in the printing of this volume.

COMMITTEES

Scientific committee

Andre ANDERS Chairman Univ. Leipzig (DE)	Ulf HELMERSSON Univ. Linköping (SE)
Thierry BELMONTE IJL, Univ. Lorraine, Nancy (FR)	Masaru HORI Univ. Nagoya (JP)
Jan BENEDIKT Univ. Bochum (DE)	Rafael JIMENEZ RIOBOO ICMM-CSIC Madrid (ES)
Annemie BOGAERTS Univ. Antwerp (BE)	Xingguo LI Univ. Peking (CN)
Peter BRUGGEMAN Univ. Minnesota (US)	Tiberiu MINEA LPGP, Univ. Paris-Sud, Orsay (FR)
Patrick CHOQUET LIST Belvaux (LU)	Ken OSTRIKOV CSIRO, Lindfield (AU)
Claudiu COSTIN Univ. Iasi (RO)	Ivan PETROV Univ. Illinois, Urbana (US)
Uros CVELBAR Jozef Stefan Institute, Ljubljana (SI)	Rony SNYDERS Univ. Mons (BE)
Hugo de HAAN Vision Dynamic (NL)	Luc STAFFORD Univ. Montreal, Québec (CA)
Jose ENDRINO Univ. Cranfield (UK)	Sabu THOMAS Mahatma Gandhi Univ. Kerala (IN)
Ursel FANTZ Univ. Augsburg (DE)	Shuyan XU NIE Singapore (SG)
Agnès GRANIER Univ. Nantes (FR)	Lenka ZAJICKOVA Univ. Masaryk, Brno (CZ)
Vasco GUERRA Univ. Lisboa (PT)	Sam ZHANG SHANYONG Univ. Nanyang (CN)
Ken HAENEN Univ. Hasselt (BE)	

Steering committee

Gérard HENRION Chairman IJL, Univ. Lorraine, Nancy (FR)	Vincent JOUSSEAUME CEA/LETI, Grenoble (FR)
Pascal ANDRE LPC, Univ. Clermont-Ferrand (FR)	Stephanos KONSTANTINIDIS UMons (BE)
Angélique BOUSQUET ICCF, Univ. Clermont Auvergne (FR)	Luc PICHON Institut Pprime, Univ. Poitiers (FR)
Corinne CHAMPEAUX IRCER, Univ. Limoges (FR)	Jean-François PIERSON IJL, Univ. Lorraine, Nancy (FR)
Richard CLERGEREAUX LAPLACE, Univ. Toulouse (FR)	Carlos PINTASSILGO IPFN, Univ. Porto (PT)
Anouk GALTAYRIES Chimie ParisTech, Paris (FR)	Joao SANTOS SOUSA LPGP, Univ. Paris-Sud, Orsay (FR)
Dirk HEGEMANN EMPA, St. Gallen (CH)	Thomas TILLOCHER GREMI, Univ. Orléans (FR)

WELCOME

Over the last decades, the community of plasma scientists has got closer and closer to the researchers and engineers in thin films science and engineering. Consequently, topics of dedicated conferences, in either plasma science or thin film research, were often overlapping. Therefore, it appeared as necessary to create a scientific event where both communities could exchange and share their knowledge and experience related to their common fields of interest. So was born the **PLA**sma **THIN** film International Union Meeting, PLATHINIUM, by merging the former three biennial events CIP (Int. Coll. Plasmas Processes), ITFPC (Innovation in Thin Film Processing and Characterization) and MIATEC (Magnetron, Ion and Arc Technology).



Among these former three international meetings, CIP was the oldest one with 21 editions held in France between 1973 and 2017. Entirely devoted to plasma science at the beginning, it progressively introduced applications of plasmas related to material processing over the last decades.

The ITFPC Conference started in 2003 and continued for the 8 editions until 2017 in Nancy (France). ITFPC followed the TATF symposium (international symposium on Trends and Applications of Thin Films) for which 7 editions were organized between 1987 and 2000.

The MIATEC conference was created in 2010 following the symposium "Magnetrons & Arcs" (in French) which started in 1999 in Mons (Belgium) as a joint event between SFV and Belvac. MIATEC was jointly organized with ITFPC in 2011, RSD (Reactive Sputter Deposition) in 2015 and CIP in 2017.

Naturally, all these scientific events organized by the French Vacuum Society (SFV) had an important overlap and therefore PLATHINIUM aims to become the biennial *rendez-vous* in plasma, plasma processing and thin films in Europe and worldwide.

Plasma processes as well as thin films and coatings are developing continuously towards advanced functionality of surfaces, and ever-new applications and complexity, thus laying foundations for various industries of today and the future. Hence, the topics of the conference are selected to address important scientific and societal challenges, to ascertain hot trend topics and to confirm continuous interest in other aspects related to plasma and thin films.

WELCOME

The ten major topics of PLATHINIUM are expected to cover the wide diversity of the domains of plasma, thin films and their applications, including plasma sources, plasma diagnostics and modelling, plasma in liquids, coating growth and modelling, nanostructured thin films, functional coatings, health and bio applications. For all participants, PLATHINIUM provides an open forum to discuss the progress and latest developments in plasmas and thin films science, engineering and technology, and applications.

Over the four days of the conference, the world-renowned scientists in the field will present 6 plenary and 8 keynote lectures. The conference program also includes 78 selected oral contributions and two poster sessions, stimulating efficient exchanges between the academic and industrial participants.

Prior to the scientific sessions, short courses will cover different aspects of plasmas and thin film science and technology in connection with the conference topics.

Have a fruitful event and a pleasant stay in Antibes and the French Riviera.

Welcome at 1st PLATHINIUM!

André ANDERS

Chair of the Scientific Committee

Gérard HENRION

Chair of the Steering Committee



TABLE OF CONTENT

GENERAL INFORMATION	3
Practical information	3
Disclaimer	3
Contacts	3
SOCIAL EVENTS	4
Get together parties	4
Conference dinner	4
Social activities	5
PROGRAM INFORMATION	6
Codes & topics	6
Key to lecture	6
Instructions for authors	7
Invited lectures	8
DETAILED PROGRAM	11
Tuesday 24 September	12
Wednesday 25 September	18
Thursday 26 September	26
Friday 27 September	32
POSTER PROGRAM	37
Poster session #1	38
Poster session #2	44
AUTHORS INDEX	49
EXHIBITORS	63
Exhibition map	63
List of exhibitors	63
Presentations	64

GENERAL INFORMATION

Practical information

▪ Official language

The conference language is English.

▪ Wi-Fi access

Indicated on your badge provided onsite.

▪ Badges

All delegates, exhibitors and visitors must wear their badges at all times to obtain admittance to the conference venue.

▪ Mobile phone

Please keep your mobile phone turned off or in silent mode in all conference rooms.

▪ Publication

A USB stick containing all abstracts (orals & posters) is distributed in the delegate's bag. The abstract book is also available on your personal registration space on the website.

▪ Tourism Office

Palais des Congrès – level 1
60 chemin des Sables
06160 Juan-les-Pins

Phone: +33 (0)4 22 10 60 01 (press 1)
www.antibesjuanlespins.com/en

▪ Opening hours

Welcome desk – level 2

Monday 23 Sept	08:00 – 20:00
Tuesday 24 Sept	08:30 – 23:00
Wednesday 25 Sept	08:00 – 18:30
Thursday 26 Sept	08:00 – 18:30
Friday 27 Sept	08:00 – 13:00

Exhibition – level 2

Tuesday 24 Sept	09:00 – 23:00
Wednesday 25 Sept	08:30 – 16:30

Disclaimer

The program is preliminary. The organizers reserve the right to alter the program if and as is deemed necessary.

The PLATHINIUM 2019 organization and/or its agents have the right for any reason beyond their control to alter or to cancel, without prior notice, the Conference or any of the arrangements, time tables, plans or other items relating directly or indirectly to the Conference. The PLATHINIUM 2019 organization and/or its agents shall not be liable for any loss, damage, expenditure or inconvenience caused as a result of such alteration or cancellation.

Contacts



Société Française du Vide

Société Française du Vide
19 rue du Renard
F75004 Paris
+33 (0)1 53 01 90 30
www.vide.org

Gweltaz HIREL

SFV Director, Event manager
gweltaz.hirel@vide.org

Hervé LEMOINE

Exhibition coordinator
herve.lemoine@vide.org

Sabra MAHDAOUI

Conference Secretary
sabra.mahdaoui@vide.org



SOCIAL EVENTS

Get together parties

✓ Included in the registration – no booking necessary

▪ **Welcome reception**

Monday 23 September - 18:30 -20:00

On Monday evening, after the short courses, come to pick your badge and conference material. The organization offers a cocktail to get together over a drink with other attendees.

▪ **Industrial evening**

Tuesday 24 September - 17:30 – 23:00

At the end of the first day of the conferences, during the Poster session #1, all the exhibitors will be pleased to open the exhibition and welcome you with a cocktail.

▪ **Poster party - session #2**

Thursday 26 September – 16:00 – 18:00

Finish the last but one day relaxed: after the afternoon break, let's talk with the presenters, of the poster session II, about their work while having a friendly drink.

Conference dinner

✗ Not included in the registration (€60 incl. VAT extra) - Booking mandatory

Wednesday 25 September at "Les pirates" Beach restaurant

Accessible by foot from the congress site, "Les Pirates" Beach Restaurant is a Treasure Island of Gastronomy, nestled in the Pine Park of Juan les Pins, just 5 min. away from the city center of Antibes. Come and discover this magic world of golden sanded beach, its pontoon and solarium on the Mediterranean ...



The long white sandy beach of approximately 2000 m² is also a mythical location where some of the most famous jazzy artists were during a legendary festival since more than 40 years. With sunbeds turquoise and white, the place is one of the largest in Juan Les Pins, including 2 piers, a solarium and private cabins.

Everything is there to make this moment unforgettable: cocktail on the pier, air-conditioned veranda in front of the sea, delicious cuisine with Provencal and Italian flavours and more than 30 years of know-how, an authentic cuisine and a quality service.



Social activities

Friday 27 September from 14:00

✓ Included in the registration / Booking mandatory

▪ Option #1 - Excursion to Grasse

International capital of Flowers and Perfume

- 14:00 / Transfer by bus from to Grasse
- 15:00 / Guided tour of the Fragonard Perfume Factory
- 16:15 / Guided tour of Grasse old town
- 17:45 / Transfer back to Juan-les-Pins

The town of Grasse is said to be the core of the Riviera as well as a model of Provençal culture. The city offers splendid vistas over the shores near Cannes. A “Cité d'Art & d'Histoire,” Grasse is known as the “Capital of Flowers and Perfume.” Clinging to sun drenched hills, this place slowly reveals its charms to those who linger in its picturesque alleyways and welcoming little squares. The historic centre confirms this architectural quality. In the 18th century, perfume making, which took over from the tanneries, blossomed. In the 19th century, flower cultivation and perfume production gave Grasse its international reputation. You will visit one of the oldest perfume factories established in a 19th century building in the heart of the old town where perfumes and soaps are crafted everyday.

▪ Option #2 - Walking tour on the coastal path “sentier de Tire-Poil”

Immerse in the nature of the Cap d'Antibes

- 14:00 / Transfer from the Congress site to a bus tour around the Cap d'Antibes
- 14:45 / Hiking on the coastal path
- 17:15 / Transfer back to Juan-les-Pins

Discover with a guide the landscapes, the points of view and the remarkable species of the Tire-Poil path. Sea Lavendar, Jupiter Beard, Common Tern... these are the suggestive names which indicate the natural wealth of this little paradise on the Mediterranean coast. You will meet native and exotic plants and will learn to respect the protected species present on the Cap d'Antibes. A naturalistic, educational, playful and sports activity for everybody!

▪ Option #3 - Excursion to Saint Paul de Vence

- 14:00 / Departure from the Congress site by coach to St Paul de Vence
- 14:45 / Guided Tour of the village
- 16:30 / Guided Tour of the Maeght Foundation
- 18:00 / Transfer back to Juan-les-Pins Convention Center

Perched on a hill overlooking the countryside and the sea, Saint-Paul de Vence is a historic village to discover and enjoy. All year round, its alleyways and ramparts are perfect for wandering and discovering the artists who have left their mark on the village, and those which continue to do so today. If Saint-Paul de Vence is a creative place, the village is also a cultural destination: its Maeght Foundation, museums and heritage are evidence of a rich history and an artistic tradition going back over a hundred years. The prestigious Maeght Modern Art Foundation, nestled in nature, brings together an important collection of paintings and sculptures of modern and contemporary art. The architecture of Josep Lluis Sert and the gardens are forming a peaceful and harmonious setting for the works of Calder, Chagall, Braque, Giacometti, Miró...



PROGRAM INFORMATION

Codes & topics

In the scientific program, the PLATHINIUM conference has been organized around 10 topics:

DEPO	Plasma - deposited coatings for optical, electronical and other functionalities
GROM	Thin films growth and modelling
HELI	Health and life science
INDU	Industrial hot topics
LIQU	Plasma and liquids
NANO	Nanomaterials and nanostructured thin films
PROC	Process control (including plasma diagnostics, plasma modelling)
SOUR	Plasma sources and electrical discharges
SURF	Plasma - surface interactions
TRIB	Plasma - deposited protective and tribological coatings

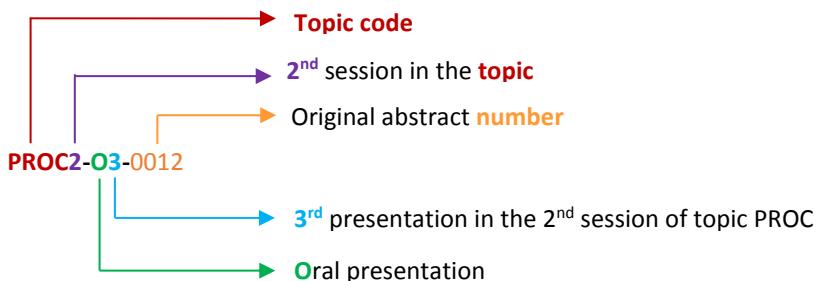
Key to lecture

Type of presentations

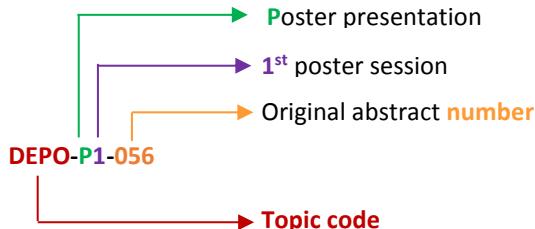
PL Plenary talk
K Keynote lecture

O Oral presentation
P Poster presentation

Lecture numbers



Poster numbers





Instructions for authors

▪ Oral Presentations

Durations (including discussions)

- Plenary talk 40 minutes
- Keynote Lectures 30 minutes
- Oral Presentations 20 minutes

Lectures must be presented **in English**.

Each speaker must ensure that presentation (including 5 min for questions) is not longer than stipulated in the program. The chairpersons will be strict on timing.

There is no preview system for the conference. All speakers have to **load their presentation file on the laptop available on the session room, preferably on the half day before the start in the session room.**

PowerPoint projection will be available in the session rooms which are equipped with a laptop computer and a projector. Overhead projection and slide projection are not available. All the hardware will be provided by the Congress to ensure consistency in technical quality and allow for quick and smooth transition between the speakers.

Please note that **only the computers provided on site can be used**.

The video files attached to the presentation must be located in the same folder as the presentation files.

Presentation's Privacy: at the end of the Congress, ALL presentations and associated files will be deleted.

▪ Poster Presentations

Each poster must be in the size of **0.85 m in width and 1.2 m in height (A0)**.

The author's name and affiliation and the title of the paper must be indicated in the top section of the poster.

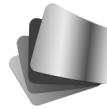
The posters will be presented and numbered according to the poster programme. The poster number will be displayed on top of the board. Writing or painting on the poster board is not allowed.

All posters will be displayed during all the conference days (Tuesday until Friday). However, focus will be made with 2 poster sessions on:

- **P1 / Session #1** with exhibition cocktail / Tuesday 24 from 17:10 until 23:00
- **P2 / Session #2** with refreshments / Thursday 26 from 16:00 until 18:00

Presenters are expected to be next to their poster during the session (P1 or P2) assigned to their poster (information sent by email & available on the detailed program & registration space).

Posters should be mounted from Tuesday 24 September 2019 at 10:00 and should be removed by 19:00 on Thursday 26 September 2019.



Invited lectures

▪ Plenary speakers

In ANTIPOLIS AUDITORIUM

Grégory ABADIAS

Prime Institute, Poitiers (FR)

Thin film growth dynamics: stress and beyond

PL2 // TUE 24 -14:00

Cristina CANAL

UPC Barcelona (ES)

*Current approach to osteosarcoma therapy with cold plasmas and biomaterials***Timo GANS**

Univ. York (UK)

Controlled plasma dynamics and chemical kinetics in low temperature plasmas for environmental & healthcare technologies

PL3 // WED 25 – 8:40

Achim von KEUDELL

Univ. Bochum (DE)

Non-equilibrium plasma chemistry - from atmospheric pressure plasmas to high pressure plasmas in liquids

PL4 // WED 25 – 14:00

Mark KUSHNER

Univ. Michigan, Ann Arbor (US)

Attempts by modeling to maintain Moore's law in microelectronics processing

PL6 // FRI 27 – 8:40

Eugen STAMATE

TU Denmark, Roskilde (DK)

Optoelectronic properties of aluminum doped zinc oxide thin films deposited by disk and rotatable magnetron sputtering cathodes at medium and radio frequency

PL1 //TUE 24 – 9:20

▪ Keynote speakers

Martin AMBERG

Empa, St.Gallen (CH)

Thermosensitive color-changing coatings for textile sensors

ANTIPOLIS AUDITORIUM

DEPO2-K1-024 // TUE 24 – 16:10

Simon BULOU

LIST, Esch sur Alzette (LU)

ELLA FITZGERALD ROOM

NANO3-K1-069 // FRI 27 – 10:30

One step gold nanoparticles synthesis and deposition from an atmospheric pressure microwave PECVD – Applications to the fast and low cost production SERS substrates



Martin FENKER

FEM, Schwäbisch Gmünd (DE)

ANTIPOLIS AUDITORIUM

DEPO4-K1-039 // WED 25 – 16:10

Influence of nitrogen incorporation on physical and electrical properties of a-C:H films deposited by a plasma beam source

Martin MICKAN

GREMI, Univ. Orléans (FR)

ANTIPOLIS AUDITORIUM

DEPO5-K1-116 // THU 26 – 14:00

Deposition of Gadolinia-doped Ceria thin films by reactive DC magnetron and High Power Impulse Magnetron Sputtering

Yevgeny RAITSES

Princeton Plasma Physics Lab., Princeton (US)

ELLA FITZGERALD ROOM

NANO1-K1-093 // WED 25 – 16:10

Synthesis of boron nitride and boron-carbon-nitride nanomaterials by arc discharge

Patrice RAYNAUD

LAPLACE, Univ. Toulouse (FR)

ELLA FITZGERALD ROOM

GROM2-K1-130 // THU 26 – 14:00

A comparative study of metal oxide and metal oxide/silica thin films deposited by LP microwave plasma process from metalorganic precursors (Zirconium Tetra tert-Butoxide and Titanium Tetra Isopropoxide)

Thibaut RICHARD

CERN, Geneva (CH)

ANTIPOLIS AUDITORIUM

PROC3-K1-106 // FRI 27 – 10:30

Numerical modelling of DC magnetron discharges applied to Nb/Cu coatings in superconducting radio-frequency cavities

Petr VASINA

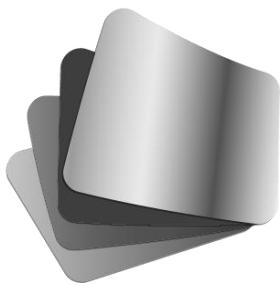
Univ. Masaryk, Brno (CZ)

ELLA FITZGERALD ROOM

TRIB2-K1-065 // TUE 24 – 16:10

Hard and fracture resistant metal-boron-carbon based coatings deposited by industrial sputtering system





PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

DETAILED PROGRAM

- Tuesday 24 September
- Wednesday 25 September
- Thursday 26 September
- Friday 27 September



Tuesday 24 September

9:00 – 12:10

9:00 Opening ceremony

ANTIOPOLIS AUDITORIUM

Chair: A. Anders

9:20 PLENARY TALK // Optoelectronic properties of aluminum doped zinc oxide thin films deposited by disk and rotatable magnetron sputtering cathodes at medium and radio frequency**E. Stamate¹, K. Norrman¹, P. Norby¹**
Technical University of DK - Kgs. Lyngby (DK)

10:00

COFFEE BREAK

DEPO 1/5 Plasma-deposited coatings for optical, electronical and other functionalities – Part I

ANTIOPOLIS AUDITORIUM

Chair: E. Stamate

10:30 DEPO1-O1-023 • Radiofrequency reactive magnetron sputtering of bismuth in an Ar/O₂/CF₄ plasma for depositing photocatalytic thin films**S. Ibrahim¹, A. Bousquet¹, P. Bonnet¹, E. Tomasella¹, M. Sarakha¹, T. Sauvage²***¹Université Clermont Auvergne, Institut de Chimie de Clermont-Ferrand (ICCF) (FR)**²CNRS/CEMHTI Site Cyclotron, Orléans (FR)*

10:50 DEPO1-O2-025 • Effects of sputtering gas environment on the nucleation and growth, optical properties, and durability of thin film silver mirrors

K. Folgner¹, C.T. Chu¹, S. Sitzman¹, Z. Lingley¹, P. Adams¹, J. Barrie¹
*Aerospace Corporation - El Segundo (US)*11:10 DEPO1-O3-048 • Thermochromic VO₂ films obtained by the oxidation of reactively sputter-deposited VN in a semi-industrial machine**A. García Wong¹, D. Pilloud¹, S. Bruyère¹, F. Capon¹, J.F. Pierson¹**
Institut Jean Lamour, Université de Lorraine - Nancy (FR)

11:30 DEPO1-O4-014 • Titanium oxide based coatings used for improving the decorative properties of orthodontic wires

V. Suciu¹, D. Cristea¹, T. Bedo¹, C. Gabor¹, J. Borges², D. Costa², F. Vaz², D. Munteanu¹*¹University Transilvania - Brasov (RO)**²University Minho - Braga (PT)*

11:50 DEPO1-O5-061 • Characterization of Nb/Cu coatings in HiPIMS with application of a positive pulse

F. Avino¹, S. Calatroni¹, A.M. Charlety¹, A. Grudiev¹, H. Neupert¹, G. Rosaz¹, A. Sublet¹, M. Taborelli¹, C. Yin Vallgren¹
CERN - Meyrin (CH)

12:10

LUNCH



Tuesday 24 September

9:00 – 12:10

10:00

COFFEE BREAK

PROC 1/3 - Process control (including plasma diagnostics, plasma modelling)

ELLA FITZGERALD ROOM

Chair: T. Richard

- 10:30 PROC1-O1-142 • On three different ways to quantify the degree of ionization in sputtering magnetrons

D. Lundin¹, A. Butler¹, N. Brenning², M. Raadu², J.T. Gudmundsson³, T. Minea¹

¹*Laboratoire de Physique des Gaz et Plasmas, CNRS/Univ. Paris-Sud - Orsay (FR)*

²*Department of Space and Plasma Physics, School of Electrical Engineering and Computer Science, KTH Royal Institute of Technology - Stockholm (SE)*

³*Science Institute, University of Iceland - Reykjavik (IS)*

- 10:50 PROC1-O2-115 • Characterization of a distributed antenna array microwave plasma used for low-temperature/large-area nanocrystalline diamond film deposition

D. Dekkar¹, F. Bénédic¹, X. Aubert¹, S. Béchu², A. Bès²

¹*LSPM-CNRS, Université Paris 13, Sorbonne Paris Cité - Villetaneuse (FR)*

²*Université Grenoble Alpes, CNRS, Grenoble INP, LPSC-IN2P3 - Grenoble (FR)*

- 11:10 PROC1-O3-067 • Time-resolved imaging of sputtered particles in multi-pulse HiPIMS discharge

J. Hnilica¹, P. Klein¹, P. Soucek¹, P. Vašina¹, R. Snyders^{2,3}, N. Britun²

¹*Department of Physical Electronics, Masaryk University - Brno (CZ)*

²*Chimie des Interactions Plasma-Surface (ChIPS), CIRMAP, Univ. de Mons (BE)*

³*Materia Nova Research Center - Mons (BE)*

- 11:30 PROC1-O4-050 • A remote plasma spectroscopy based method for monitoring of volatile chemicals in a vacuum environment

B. Kurian¹, J. Brindley¹, D. Monaghan¹, B. Daniel¹, V. Bellido-Gonzalez¹
Gencoal Ltd - Liverpool (UK)

- 11:50 PROC1-O5-003 • Density of N and H atoms in R/x%(N_2 -5%H₂) (R = Ar or He) microwave afterglows

A. Ricard¹, J.P. Sarrette¹

Laplace-Univ. Toulouse-CNRS - Toulouse (FR)

12:10

LUNCH



Tuesday 24 September

14:00 – 15:40

Chair: T. Czerwiec

ANTIPOLIS AUDITORIUM

- 14:00 **PLENARY TALK //** Structure, stress and physical properties of Mo-Al-N thin films deposited by reactive magnetron sputtering
G. Abadias¹, F. Angay¹, D. Eyidi¹, S. Camelio¹
Institut Pprime, CNRS-Université de Poitiers - Futuroscope-Chasseneuil (FR)

SOUR 1/1 Plasma sources and electrical discharges

ANTIPOLIS AUDITORIUM

Chair: A. Lacoste

- 14:40 SOUR1-O1-059 • A novel plasma jet with RF and HF coupled electrodes
A. Patelli¹, F. Tampieri¹, E. Marotta¹, E. Cattaruzza², B. Zaniol³,
P. Scopece⁴
¹*University of Padova - Padova (IT)*
²*University of Venice - Venezia (IT)*
³*Consorzio RFX - Padova (IT)*
⁴*Nadir srl - Venezia (IT)*

- 15:00 SOUR1-O2-072 • Bipolar high-power pulsed magnetron sputtering (BPH) of titanium dioxide: influence of electrical parameters on the discharge and film properties

M. Michiels¹, A. Hemberg¹, Y. Paint¹, N. Britun², S. Konstantinidis²,
R. Snyders²
¹*Materia Nova R&D center - Mons (BE)*
²*Chimie des Interactions Plasma-Surface (ChIPS), CIRMAP, Univ. de Mons (BE)*

- 15:20 SOUR1-O3-153 • HiPIMS electron properties by Thomson uncoherent scattering and PIC-MCC modeling

T. Minea¹, S. Tsikata², A. Revel¹, B. Vincent²
¹*LPGP CNRS-Université Paris-Saclay - Orsay (FR)*, ²*ICARE, CNRS - Orléans (FR)*

15:40

COFFEE BREAK



Tuesday 24 September

14:00 – 15:40

TRIB 1/5 Plasma-deposited protective and tribological coatings – Part I

ELLA FITZGERALD ROOM

Chair: T. Czerwiec

- 14:40 TRIB1-O1-005 • Mechanical properties and corrosion behaviour of DLC monolayers and multilayers deposited over nitrided martensitic stainless steel

S. Brühl¹, E.L. Dalibón¹, V.J. Trava-Airoldi², A. Cabo³

¹UTN National University of Technology - Concepción Del Uruguay (AR)

²INPE - São José Dos Campos, Sp (BR)

³IONAR S.A. - San Martín (AR)

- 15:00 TRIB1-O2-060 • Optimization of AlCrN monolayers and Cr/CrN/AlCrN multilayers for metal forming and machining applications

Y. Zhang¹, C. Nouveau¹, J. Outeiro¹, A. Besnard¹, B. Jullière², S. Dezecot²

¹Arts et Métiers ParisTech - Cluny (FR)

²EVATEC Tools - Thionville (FR)

- 15:20 TRIB1-O3-158 • Surface pretreatment effects on Tantalum coating microstructure when deposited on biomedical NiTi wires

B. Pace¹, J. Cairney¹

The University of Sydney - Camperdown (AU)

15:40

COFFEE BREAK



Tuesday 24 September

16:10 – 17:20

**DEPO 2/5 Plasma-deposited coatings for optical, electronical
and other functionalities – Part II**

ANTIPOlis AUDITORIUM

Chair: R. Clergereaux

- 16:10 **KEYNOTE // DEPO2-K1-024** • Thermosensitive color-changing coatings for textile sensors

M. Amberg¹, D. Leutenegger¹, D. Hegemann¹.

Empa - St. Gallen (CH)

- 16:40 **DEPO2-O2-016** • Concentrated solar power plants need plasma coatings for efficient solar energy conversion

D. Ngoue¹, A. Carling-Plaza², A. Diop¹, A. Grosjean¹, V. Pares¹,

A. Soum-Glaude², S. Quoizola¹, E. Hernandez¹, L. Thomas¹

¹PROMES-CNRS-UPVD - Perpignan (FR)

²PROMES-CNRS - Perpignan (FR)

- 17:00 **DEPO2-O3-078** • Optimizing material properties of sputter deposited optical interference coatings by plasma assist

S. Schwyn Thöny¹, S. Gees¹, E. Schuengel¹

Evatec AG - Trübbach (CH)

17:20

POSTER SESSION #1
& EXHIBITION COCKTAIL



Tuesday 24 September

16:10 – 17:20

TRIB 2/5 Plasma-deposited protective and tribological coatings – Part II

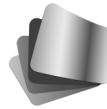
ELLA FITZGERALD ROOM

Chair: G. Abadias

- 16:10 **KEYNOTE // TRIB2-K1-065** Hard and fracture resistant metal-boron-carbon based coatings deposited by industrial sputtering system
P. Vasina¹, M. Kroker¹, P. Matej¹, M. Fekete¹, L. Zabransky¹,
P. Soucek¹, V. Bursikova¹
Masaryk university - Brno (CZ)
- 16:40 TRIB2-O2-013 • Non-reactive HiPIMS of oxide ceramics for carbide cutting tools
B. Gaedike¹, R. Gadow², F. Kern², A. Killinger², M. Luik¹
¹*Hartmetall-Werkzeugfabrik Paul Horn GmbH - Tübingen (DE)*
²*Institute for Manufacturing Technologies of Ceramic Components and Composites, University of Stuttgart (DE)*
- 17:00 TRIB2-O3-111 • Multilayered PVD coatings for erosion protection of Carbon Fiber Reinforced Polymers
B. Coto¹, L. Mendizabal¹, L. Selegard², H. Kling², F. Pagano¹, R. Ortiz¹
¹*IK4-TEKNIKER - Eibar (ES)*
²*SAAB - Linköping (SE)*

17:20

POSTER SESSION #1
& EXHIBITION COCKTAIL



Wednesday 25 September

8:40 – 10:00

Chair: J. Santos Sousa

ANTIPOLIS AUDITORIUM

- 8:40 **PLENARY TALK //** Current approach to osteosarcoma therapy with cold plasmas and biomaterials
C. Canal
UPC Barcelona (ES)

TRIB 3/5 Plasma-deposited protective and tribological coatings – Part III

ANTIPOLIS AUDITORIUM

Chair: P. Vasina

- 9:20 TRIB3-O1-129 • Exploration of new PVD coatings resistant to solid particles erosion
M-A. Leroy¹, Y. Gachon¹, C. Pupier¹
IREIS / Groupe HEF - Andrézieux Bouthéon (FR)
- 9:40 TRIB3-O2-144 • New insight in corrosion resistance of TiO₂ thin films obtained by PVD sputtering in an inverted cylindrical magnetron (ICM)
M. Mantel¹, C. Esparza Contro¹, C. Vachey², G. Berthomé¹,
L. Latu Romain¹
¹Univ. Grenoble Alpes, CNRS, Grenoble INP, SIMaP - Grenoble (FR),
²Ugitech S.A., Avenue Paul Girod - Ugine (FR)

10:00

COFFEE BREAK



Wednesday 25 September

8:40 – 10:00

HELI 1/1 Health and life science

ELLA FITZGERALD ROOM

Chair: M. Amberg

- 9:20 HELI1-O1-124 • Ageing of amine-rich plasma polymer coatings and their usage for enhancement of vascular cell proliferation on polycaprolactone nanofibers

L. Blahová¹, M. Michlicek², J. Medalova³, P. Cernochova³, M. Parizek⁴, I. Kopova⁴, L. Bacakova⁴, L. Zajickova¹

¹*RG Plasma Technologies, CEITEC – Central European Institute of Technology, Masaryk University - Brno (CZ),*

²*Dep. of Physical Electronics, Faculty of Science, Masaryk University - Brno (CZ),*

³*Dep. of Experimental Biology, Faculty of Science, Masaryk University - Brno (CZ)*

⁴*Department of Biomaterials and Tissue Engineering, Institute of Physiology of the Academy of Sciences of the CZ - Prague (CZ)*

- 9:40 HELI1-O2-161 • Optimization of helium cold plasma jets for new anti-tumor treatments

J. Santos Sousa¹, K. Sklias¹, K. Gazeli¹, G. Bauville¹, M. Fleury¹, P.M. Girard²

¹*LPGP, CNRS, Univ. Paris-Sud, Université Paris-Saclay - Orsay (FR),*

²*Institut Curie, PSL Research University, Univ. Paris-Sud, Université Paris-Saclay, CNRS UMR3347, INSERM U1021 - Orsay (FR)*

10:00

COFFEE BREAK



Wednesday 25 September

10:30 – 12:10

**DEPO3/5 Plasma-deposited coatings for optical, electronical
and other functionalities – Part III**
ANTIPOlis AUDITORIUM

Chair: M. Fenker

- 10:30 DEPO3-O1-102 • XRF and GDOES synergy for layer quantification
S. Gaiaschi¹, J. Marciano¹, M. Stanley², P. Chapon¹
HORIBA FR - Palaiseau (FR), ²EDF-IPVF - Palaiseau (FR)
- 10:50 DEPO3-O2-127 • Nb doped-TiO₂ thin films deposited by Plasma Enhanced Chemical Vapour Deposition at low substrate temperature for photocatalytic applications
B. Dey¹, S. Bulou¹, T. Gaulain¹, W. Ravisy², M. Richard-Plouet²,
A. Gouillet², A. Granier², P. Choquet¹
¹*LU Institute of Science and Technology - Esch Sur Alzette (LU)*
²*Institut des Matériaux Jean Rouxel - Nantes (FR)*
- 11:10 DEPO3-O3-088 • New adhesive joint elaborated by pulsed RF plasma polymerization
M. Ji¹, L. Benyahia¹, F. Poncin-Epaillard¹
Institut des Molécules et Matériaux du Mans (IMMM), UMR n°6283 Le Mans Université, Le Mans (FR)
- 11:30 DEPO3-O4-100 • Deposition of titanium dioxide films by atmospheric pressure plasma torch: design of the layer in the view of photovoltaic applications
A. Perraudeau¹, C. Dublanche-Tixier¹, P. Tristant¹, C. Chazelas¹,
S. Vedraine², B. Ratier²
¹*Université de Limoges, CNRS, IRCCYB, UMR 7315 - Limoges (FR)*
²*Université de Limoges, CNRS, XLIM, UMR 7252 - Limoges (FR)*
- 11:50 DEPO3-O5-140 • Optimization of surface properties of wood modified by cold remote N₂/O₂ microwave plasma process
B. Mutel¹, C. Jama², M. Bigan³
¹*IEMN, Team P2M, University of Lille - Villeneuve D'ascq (FR)*
²*UMET, Ecole Nationale Supérieure de Chimie de Lille - Villeneuve-D'ascq (FR)*
³*Institute Charles Violette, Team ProBioGen, University of Lille (FR)*

12:10

LUNCH



Wednesday 25 September

10:30 – 12:10

INDU 1/1 Industrial hot topics

ELLA FITZGERALD ROOM

Chair: P. Choquet

- 10:30 INDU1-O1-190 • Integrated atom Probe/tEBSD for grain boundary analysis in a thermal barrier coating
Y. Chen¹, A. Bui², K. Rice¹, P.H. Clifton¹, T.J. Prosa¹
¹CAMECA Instrument Inc. - Madison (US)
²CAMECA SAS - Gennevilliers (FR)
- 10:50 INDU1-O2-028 • PECVD/ECR/HWCVD multichamber system with robotic substrate handling system for deposition of thin film electronic devices
A. Jacquemot¹, P. Rava²
¹MICROTEST - Sérignan (FR)
²ELETTRORAVA - Venaria Reale (IT)
- 11:10 INDU1-O3-167 • Facilitated sputter deposition processing of nitrides, oxides, ceramics, TCO's and other complex thin films by using a refined power supply technology
G. Eichenhofer
^{4A-PLASMA - Holzgerlingen (DE)}
- 11:30 INDU1-O4-138 • Advanced HIPIMS coatings through Kick pulse technology
Advanced HIPIMS coatings through Kick pulse technology
J. Hrebik
Kurt J. Lesker Company - Jefferson Hills (US)
- 11:50 INDU1-O5-021 • High temperature oxidation protection of g-based TiAl by sputtered Al-O-F films
M. Cavarroc¹, F. Bergeron², S. Loquai², E. Bousser², S. Knittel³,
L. Martinu², J.E. Sapieha²
¹Safran Tech, Materials & Processes department - Magny-les-Hameaux (FR),
²Ecole Polytechnique de Montréal - Montréal (CA)
³Safran Aircraft Engines - Evry (FR)

12:10

LUNCH



Wednesday 25 September

14:00 – 15:40

Chair: T. Minea

ANTIPOLIS AUDITORIUM

- 14:00 **PLENARY TALK //** Non-equilibrium plasma chemistry - from atmospheric pressure plasmas to high pressure plasmas in liquids
A. Von Keudell¹, T. Urbanietz¹, C. Stewig¹, G. Katharina¹, H. Julian¹.
Ruhr University Bochum - Bochum (DE)

GROM 1/2 Thin films growth and modelling

ANTIPOLIS AUDITORIUM

Chair: G. Marcos

- 14:40 GROM1-O1-007 • Hot target magnetron sputtering applied to oxide thin film growth
R. Graillot Vuillecot¹, C. Cachoncinlle¹, E. Millon¹, A.L. Thomann¹,
A. Caillard¹
GREMI UMR 7344 Université d'Orléans - CNRS - Orléans (FR)
- 15:00 GROM1-O2-036 • Controlling surface morphology and properties by nanocrystalline/amorphous competitive growth in thin films
A. Borroto^{1,2}, S. Bruyère¹, S. Migot¹, J.F. Pierson¹, A.C. García-Wong¹,
T. Gries¹, F. Mücklich³, D. Horwat¹
¹Institut Jean Lamour (UMR CNRS 7198), Univ. de Lorraine, Nancy (FR)
²Dep. of Materials Science and Engineering, Saarland University, Saarbrücken, (DE)
³Dep. of Materials Science and Engineering, Saarland University, Saarbrücken, (DE)
- 15:20 GROM1-O3-081 • Virtual Coater: On the implementation of specific algorithms to predict and optimize coating uniformity on 3D parts in motion
M. Evrard¹, S. Lucas¹, A. Besnard²
¹University of Namur - NISM - LARN - Namur (BE)
²ENSAM - LaBoMaP - Cluny (FR)

15:40

COFFEE BREAK



Wednesday 25 September

14:00 – 15:40

LIQU 1/1 Plasma and liquids

ELLA FITZGERALD ROOM

Chair: A-L. Thomann

- 14:40 LIQU1-O1-042 • Internal micro-discharges during the plasma Electrolytic oxidation process: evidence and effects on the coating formation
V. Ntomprougkidis¹, J. Martin¹, I.V. Bardin², A. Nominé³, C. Noël⁴, G. Henrion¹

¹Institute Jean Lamour - LabEx DAMAS - University of Lorraine - Nancy (FR)

²National University of Science and Technology MISiS - Moscow (RU)

³Dep. of Nanophotonics and Metamaterials, ITMO University - St. Petersburg (RU)

⁴Institute Jean Lamour - University of Lorraine - Nancy (FR)

- 15:00 LIQU1-O2-123 • Synthesis and electrocatalytic behavior of Pt-based nano-catalyst obtained via magnetron sputtering onto vegetal glycerin
V. Orozco¹, J. Bigarre², S. Cuynet³, P. Brault¹, A. Caillard¹
¹Groupe de recherches sur l'énergétique des Milieux Ionisés (GREMI) UMR 7344, Université d'Orléans / CNRS - Orléans (FR)
²CEA DAM, Le Ripault - Monts (FR),
³Institut Jean Lamour (IJL) UMR 7198, Université de Lorraine / CNRS - Nancy (FR)

- 15:20 LIQU1-O3-031 • Synergy between Cold Atmospheric Plasma and Nano-Photocatalyst for Pharmaceuticals Removal in Drinking Water
M. El Shaer¹, M. Eldaly¹, G. Heikal², Y. Sharaf³, H. Diab⁴, B. Liu⁵, M. Mobasher¹, A. Rousseau⁵
¹PEARLZ (Plasma & Energy Applications Research Laboratory, Zagazig), Faculty of Engineering, Zagazig University (EG)
²Dep. of Environmental Engineering, Faculty of Engineering, Zagazig University (EG)
³Dep. of Analytical Chemistry, Faculty of Pharmacy, Zagazig University (EG)
⁴Dep. of Microbiology, Faculty of Medicine, Zagazig University (EG)
⁵LPP, Ecole Polytechnique, CNRS, Sorbonne Université, Université Paris-Saclay, Palaiseau (FR)

15:40

COFFEE BREAK



Wednesday 25 September

16:10 – 18:00

**DEPO4/5 Plasma-deposited coatings for optical, electronical
and other functionalities – Part IV**

ANTIPOLIS AUDITORIUM

Chair: S. Konstantinidis

- 16:10 **KEYNOTE // DEPO4-K1-039** • Influence of nitrogen incorporation on physical and electrical properties of a-C:H films deposited by a plasma beam source

M. Fenker¹, J. Julin², K. Petrikowski¹, A. Richter¹

¹fem Research Institute for Precious Metals and Metal Chemistry - Schwäbisch Gmünd (DE)

²Helmholtz-Zentrum Dresden-Rossendorf - Dresden (DE)

- 16:40 DEPO4-O2-022 • Atmospheric-Pressure Synthesis of Atomically Smooth, Conformal, and Ultrathin Low-k Polymer Insulating Layers by Plasma-Initiated CVD

D. Abessolo Ondo¹, F. Loyer¹, F. Werner², R. Leturcq¹, D. Phillip², N.D. Boscher¹

¹LU Institute of science and technology - Esch-sur-Alzette (LU)

²University of LU - Esch-sur-Alzette (LU)

- 17:00 DEPO4-O3-096 • iCVD pore filling: a way to limit plasma damage during porous low-k integration

M. Van-Straaten^{1,2}, A. Tavernier¹, M. Lagrange¹, B. Assie¹, C. Ratin¹, A. Ben Hadj Mabrouk¹, M. Veillerot¹, F. D'agosto³, N. Posseme¹, V. Jousseaume¹

¹Univ. Grenoble Alpes - Grenoble (FR)

²CEA, LETI, MINATEC Campus - Grenoble, (FR)

³Université de Lyon, Univ Lyon 1, CPE Lyon, CNRS, UMR 5265, C2P2 (Chemistry, Catalysis, Polymers & Processes) - Villeurbanne (FR)

- 17:20 DEPO4-O4-166 • High performance hard magnetic Nd₂Fe₁₄B thin films by pulsed laser deposition

T. Nguyen Van¹, N. Dempsey², C. Champeaux¹, F. Dumas-Bouchiat¹

¹University of Limoges, CNRS, IRCER, UMR 7315 - Limoges (FR)

²Institut Néel, CNRS-UJF - Grenoble (FR)

- 17:40 DEPO4-O5-168 • Elaboration and thermoelectric properties of CuCrO₂:Mg and CuFeO₂:Mg thin films deposited by RF sputtering

L. Presmanes¹, Y. Thimont¹, I. Sinnarasa¹, A. Barnabe¹, P. Tailhades¹

¹CIRIMAT UMR CNRS 5085 - Toulouse (FR)

18:00

19:30

CONFERENCE DINNER

AT "LES PIRATES" BEACH RESTAURANT



Wednesday 25 September

16:10 – 18:00

NANO 1/3 Nanomaterials and nanostructured thin films

ELLA FITZGERALD ROOM

Chair: A. Granier (provisional)

- 16:10 KEYNOTE // NANO1-K1-093 • Synthesis of boron nitride and boron-carbon-nitride nanomaterials by arc discharge

Y. Raitses¹, S. Yatom¹, R. Selinsky², Y.W. Yeh², A. Khrabryi¹, I. Kaganovich¹, B. Koel², B. Santra², R. Car², P. Krstic³, L. Han³

¹*Princeton Plasma Physics Laboratory - Princeton (US)*

²*Princeton University - Princeton (US), ³SUNY at Stony Brook (US)*

- 16:40 NANO1-O2-076 • Dichroic optical properties of non-noble metal nanostructures prepared by glancing-angle deposition onto nanorippled surfaces

D. Babonneau¹, S. Camelio¹, F. Pailloux¹, A. Fafin¹, G. Abadias¹, P. Patsalas²

¹*Institut Pprime, CNRS-Université de Poitiers - Poitiers (FR)*

²*Department of Physics, Aristotle University of Thessaloniki (GR)*

- 17:00 NANO1-O2-092 • Functional study of carbon nanotubes as adhesives for micro-objects

L. Zajickova¹, M. Elias², T. Vystavel³, P. Poloucek³, D. Necas¹, P. Kaushik¹, P. Klapetek⁴

¹*Masaryk University - Brno (CZ)*

²*Brno University of Technology - Brno (CZ)*

³*ThermoFisher - Brno (CZ)*

⁴*Czech Metrology Institute - Brno (CZ)*

- 17:20 NANO1-O3-095 • Hexagonal boron nitride thin film synthesis by micro hollow cathode discharges

H. Kabbara¹, S. Kasri¹, V. Mille¹, A. Tallaire¹, O. Brinza¹, G. Lombardi¹, C. Lazzaroni¹

LSPM CNRS UPR3407, Laboratoire des Sciences des procédés et des matériaux, Université Paris13, Sorbonne Paris Cité, Villejuif (FR)

- 17:40 NANO1-O5-110 • Nano ZnO and ZnO₂ Deposition by HIPIMS Magnetron Sputtering at Cryogenic Substrate Temperatures

MODIFIED

J. Purans¹, M. Zubkins¹, R. Kalendarev¹, A. Azens¹
Institute of Solid State Physics University of Latvia - Riga (LV)

18:00

19:30

CONFERENCE DINNER
AT "LES PIRATES" BEACH RESTAURANT



Thursday 26 September

8:40 – 10:00

Chair: A. Bousquet

ANTIPOLIS AUDITORIUM

- 8:40 **PLENARY TALK //** Controlled plasma dynamics and chemical kinetics in low temperature plasmas for environmental & healthcare technologies
T. Gans
Univ. York (UK)

TRIB 4/5 Plasma-deposited protective and tribological coatings

ANTIPOLIS AUDITORIUM

Chair: A. Bousquet

- 9:20 TRIB4-O1-047 • Active corrosion protection for 3D-printed aluminum alloys by atmospheric pressure plasma deposition of cerium containing thin films
A.M. Schwan¹, A. Pfuch², K. Horn², A. Hinterer³, P. Stögmüller³,
S. Proschwitz⁴, M. Putzschke⁴, J.M. Lackner¹, W. Waldhauser¹
¹JOANNEUM RESEARCH Forschungsgesellschaft m.b.H. - Graz (AT)
²INNOVENT e.V. - Jena (DE)
³INOCON Technologie G.m.b.H. - Attnang-Puchheim (AT)
⁴MAICOM Quarz G.m.b.H. - Posterstein (DE)

- 9:40 TRIB4-O2-058 • Mechanical properties of nanocomposite thin films produced with a reactor-injector: From stiff to soft coatings
G. Carnide^{1,2}, T. Sadek³, J. Bardon⁴, D. Ruch⁴, L. Stafford³, M. Kahn¹,
R. Clergereaux⁵
¹LCC - Toulouse (FR)
²LAPLACE (US)
³UDEM - Montreal (CA)
⁴LIST (LU)
⁵LAPLACE - Toulouse (FR)

10:00

COFFEE BREAK



Thursday 26 September

8:40 – 10:00

SURF 1/2 Plasma-surface interactions

ELLA FITZGERALD ROOM

Chair: A. Caillard

- 9:20 SURF1-O1-070 • Hyperspectral Raman imaging applied to fundamental studies of plasma-graphene interactions in pulsed and continuous argon plasmas at low pressure
P. Vinchon¹, G. Robert Bigras¹, X. Glad¹, C. Allard¹, R. Martel¹, L. Stafford¹
Université de Montréal - Montréal (CA)
- 9:40 SURF1-O2-154 • Effect of different nitrogen-containing plasma used for N-doping of graphene nanowalls
N. Marath Santhosh^{1,2}, G. Filipic¹, U. Cvelbar¹
¹*Jozef Stefan Institute, - Ljubljana (SI)*
²*Jozef Stefan International Postgraduate School, - Ljubljana (SI)*

10:00

COFFEE BREAK



Thursday 26 September

10:30 – 12:10

**PROC 2/3 Process control (including plasma diagnostics,
plasma modelling)**

ANTIPOlis AUDITORIUM

Chair: T. Gans (provisional)

- 10:30 PROC2-O1-071 • Synthesis of zirconium oxide thin films by reactive HiPIMS under peak current regulation

S. Konstantinidis¹, S. Adzhani², N. Britun¹, A. Panepinto¹, M. Yang²,
T. Shimizu²

¹*Plasma-Surface Interaction Chemistry, University of Mons - Mons (BE)*

²*Division of Mechanical System Engineering, Graduate School of System Design,
Tokyo Metropolitan University (JP)*

- 10:50 PROC2-O2-066 • Understanding and influencing energies of ions incident onto substrate in bipolar HiPIMS discharges

T. Kozak¹, A.D. Pajdarova¹, J. Capek¹, P. Mares², M. Cada³, Z. Hubicka³
¹*Department of Physics and NTIS – European Centre of Excellence, University of West Bohemia - Plzen (CZ)*

²*HVM Plasma, s.r.o. - Praha (CZ)*

³*Institute of Physics, Academy of Sciences of the CZ - Praha (CZ)*

- 11:10 PROC2-O3-131 • Deposition process for low temperature growth of VO₂ thin films on large area using the microwave plasma-assisted reactive sputtering technique

A. Lacoste¹, A. Bès¹, R. Yang¹

LPSC, Université Grenoble-Alpes, CNRS/IN2P3 - Grenoble (FR)

- 11:30 PROC2-O4-169 • On the effect of stationary magnetic field on spatial distribution of deposition rate and ionized flux fraction in the HiPIMS discharge

H. Hajihoseini¹, J.T. Gudmundsson¹, D. Lundin², M. Cada³, Z. Hubicka³

¹*Science institute, University of Iceland - Reykjavik (IS)*

²*LPGP, Université Paris-Sud - Orsay (FR)*

³*Institute of Physics ASCR - Prague (CZ)*

- 11:50 PROC2-O5-121 • Influence of gas pulsed injection in Dielectric Barrier Discharges at atmospheric pressure

L. Cacot¹, M. Kahn², R. Clergereaux¹, N. Naudé¹, L. Stafford³

¹*LAPLACE, Université de Toulouse, CNRS - Toulouse (FR)*

²*CNRS, LCC (Laboratoire de Chimie de Coordination) - Toulouse (FR)*

³*Département de Physique - Université de Montréal - Montréal (CA)*

12:10

LUNCH



Thursday 26 September

10:30 – 12:10

NANO 2/3 Nanomaterials and nanostructured thin films

ELLA FITZGERALD ROOM

Chair: L. Zajickova (provisional)

- 10:30 NANO2-O1-041 • A novel one-step approach for nanocomposite thin films coupling PECVD and colloidal solutions

M. Mitronika¹, J. Profili², A. Goulet¹, L. Stafford², A. Granier¹, M. Richard-Plouet¹

¹*Institut des Matériaux Jean Rouxel (IMN), Université de Nantes, CNRS, Nantes (FR)*

²*Département de Physique, Université de Montréal, Montréal, Québec, Montréal (CA)*

- 10:50 NANO2-O2-105 • Plasma-based modification of membranes with nanoparticles for versatile oil/water separation

A. Shukurov¹, M. Vaidulych¹, A. Shelemin¹, J. Hanuš¹, I. Khalakhan², P. Pleskunov¹, O. Kylián¹, H. Biederman¹

¹*Charles University, Faculty of Mathematics and Physics, Department of Macromolecular Physics - Prague (CZ)*

²*Charles University, Faculty of Mathematics and Physics, Department of Surface and Plasma Science - Prague (CZ)*

- 11:10 NANO2-O3-132 • An innovative approach for micro/nano structuring plasma polymer films

N. Vinx¹, P. Damman², D. Moerman³, P. Leclère³, C. Satriano⁴, R. Snyders¹, D. Thiry¹

¹*Chimie des Interactions Plasma-Surface (ChIPS), University of Mons - Mons (BE)*

²*Laboratoire Interfaces et Fluides Complexes (Influx), University of Mons - Mons (BE)*

³*Chimie des Matériaux Nouveaux (CMN), University of Mons - Mons (BE)*

⁴*Laboratory of Hybrid NanoBioInterfaces (NHIL), University of Catania - Catania (IT)*

- 11:30 NANO2-O4-165 • Pulsed laser nanoparticles source and thin films deposition to tune vanadium dioxide properties

C. Champeaux¹, M. Gaudin¹, R. Boyer¹, F. Dumas-Bouchiat¹
University of Limoges, CNRS, IRCE, UMR7315 - Limoges (FR)

- 11:50 NANO2-O5-101 • Electron emission characteristic study on carbon-based very thin films prepared by RF magnetron sputtering

J. Huran¹, N.I. Balalykin¹, M.A. Nozdrin¹, V. Sasinková², E. Kováčová³, A.P. Kobzev¹, A. Kleinová

¹*Joint Institute for Nuclear Research - Dubna (RU)*

²*Institute of Chemistry, SAS - Bratislava (SK)*

³*Institute of Electrical Engineering, SAS - Bratislava (SK)*

⁴*Polymer Institute, SAS - Bratislava (SK)*

12:10

LUNCH



Thursday 26 September

14:00 – 16:00

**DEPO 5/5 Plasma-deposited coatings for optical,
electronical and other functionalities**

ANTIOPOLIS AUDITORIUM

Chair: J-F. Pierson

- 14:00 **KEYNOTE // DEPO5-K1-116** • Deposition of Gadolinia-doped Ceria thin films by reactive DC magnetron and High Power Impulse Magnetron Sputtering

M. Mickan¹, A. Caillard¹, T. Lecas¹, P. Coddet², J. Vulliet²,

H. Lecocq³, T. Sauvage³, A.L. Thomann¹

¹*GREMI, UMR7344 CNRS/Université d'Orléans (FR)*

²*CEA DAM, Le Ripault - Monts (FR)*

³*CEMHTI, UPR3079 du CNRS - Orléans (FR)*

- 14:30 **DEPO5-O2-057** • Influence of transition metal dopants on the reactive HiPIMS deposition of γ -Al₂O₃ thin films

H. Riedl¹, S. Kagerer¹, L. Zauner¹, T. Wojcik¹, S. Kolozsvári²,

J. Capek³, T. Kozák³, P. Zeman³, P.H. Mayrhofer¹

¹*Institute of Materials Science and Technology, TU Wien - Wien (AT)*

²*Plansee Composite Materials GmbH - Lechbruck Am See (DE)*

³*Department of Physics and NTIS, European Center of Excellence, University of West Bohemia - Plzen (CZ)*

- 14:50 **DEPO5-O3-162** • Metal-to-insulating transition tuning in reactively sputter-deposited epitaxial V₂O₃ thin films

S. Shayestehaminzadeh¹, E.B. Thorsteinsson², A.S. Ingason³,

F. Magnus², U.B. Arnalds²

¹*Technovation Center, AGC Glass Europe - Gosselies (BE)*

²*Science Institute, University of Iceland - Reykjavík (IS)*

³*Grein Research ehf. - Reykjavík (IS)*

- 15:10 **DEPO5-O4-037** • Cathodic arc deposition of V₂O₃ films and their application in quench protection of high-temperature superconducting magnets

Q. Ji¹, Z. Yang¹, X. Wang¹, A. Anders²

¹*Lawrence Berkeley National Laboratory - Berkeley (US)*

²*Leibniz Institute of Surface Engineering (IOM) - Leipzig (DE)*

15:30

COFFEE BREAK

16:00

POSTER SESSION #2

18:00



Thursday 26 September

14:00 – 16:00

GROM 2/2 Thin films growth and modelling

ELLA FITZGERALD ROOM

Chair: S. Brühl

- 14:00 **KEYNOTE // GROM2-K1-130** • A comparative study of metal oxide and metal oxide/silica thin films deposited by LP microwave plasma process from metalorganic precursors (Zirconium Tetra tert-Butoxide and Titanium Tetra Isopropoxide)

P. Raynaud¹, I. Martinko¹, R. Alvarez², A. Palmero²

¹Laboratoire Laplace - CNRS - Université Toulouse - Toulouse (FR)

²Spanish Council of Research (CSIC), Materials Science Institute of Seville (ES)

- 14:30 **GROM2-O2-062** • Nanostructure and photocatalytic activity of Plasma-Enhanced Chemical Vapour Deposited anatase TiO₂ on polymer substrates

W. Ravisy¹, B. Dey², D. Li¹, S. Bulou², P. Choquet², N. Gautier¹,
A. Gouillet¹, M. Richard-Plouet¹, A. Granier¹

¹IMN, Univ. de Nantes, UMR CNRS 6502, Nantes (FR)

²Materials Research and Technology Dep., LIST - Esch-sur-Alzette (LU)

- 14:50 **GROM2-O3-125** • Analysis of nanoscopic defects in SiO_x like plasma polymer films by means of positron annihilation spectroscopy

C. Hoppe¹, F. Mitschker², P. Awakowicz², T. De Los Arcos¹,
G. Grundmeier¹

¹Technical and Macromolecular Chemistry, University of Paderborn - Paderborn (DE)

²Electrical Engineering and Plasma Technology, Ruhr-University Bochum (DE)

- 15:10 **GROM2-O4-012** • Numerical and experimental investigation of the deposition of plasma polymerized films on low-vapour-pressure liquids

S. Gaiser¹, D. Hegemann¹

Empa, Swiss Federal Laboratories for Materials Science and Technology, Advanced Fibers, Plasma & Coating Group - St. Gallen (CH)

15:30

COFFEE BREAK

16:00

POSTER SESSION #2

18:00



Friday 27 September

8:40 – 10:00

Chair: L. Stafford (provisional)

ANTIPOLIS AUDITORIUM

- 8:40 **PLENARY TALK //** Attempts by modeling to maintain Moore's law in microelectronics processing
M. Kushner
Univ. Michigan, Ann Arbor (US)

TRIB 5/5 Plasma-deposited protective and tribological coatings

ANTIPOLIS AUDITORIUM

Chair: E. Tomasella

- 9:20 TRIB5-O1-113 • Low temperature conformal deposition of nanocrystalline diamond on three-dimensional substrates for biomedical applications
F. Bénédic¹, D. Dekkar¹, C. Falentin-Daudré², O. Brinza¹, R. Issaoui¹, J. Achard¹
¹LSPM-CNRS, UPR 3407, Université Paris 13, Sorbonne Paris Cité - Villetteuse (FR)
²LBPS-CSPBAT, UMR 7244, Univ. Paris 13, Sorbonne Paris Cité - Villetteuse (FR)

- 9:40 TRIB5-O2-141 • Plasma-assisted patterning on metal surfaces for tribological applications
G. Marcos¹, A. Pavlik², J. Vincent³, M. Coulibaly³, J. Martin¹, S. Philippon³, T. Czerwic¹
¹Institut Jean Lamour - Nancy (FR)
²Institut Jean Lamour/LEM3 - Nancy (FR)
³LEM3 - Metz (FR)

10:00

COFFEE BREAK



Friday 27 September

8:40 – 10:00

SURF 2/2 Plasma-surface interactions

ELLA FITZGERALD ROOM

Chair: C. Champeaux (provisional)

- 9:20 SURF2-O1-026 • Atomic Layer Etching at cryogenic temperature
G. Antoun¹, P. Lefaucheur¹, T. Tilloccher¹, R. Dussart¹, S. Tahara²,
K. Yamazaki³, K. Yatsuda³, J. Faguet⁴, K. Maekawa⁴
¹*GREMI, Orleans University-CNRS - Orleans (FR)*
²*Tokyo Electron Miyagi Limited - Miyagi (JP)*
³*Tokyo Electron Limited - Tokyo (JP)*
⁴*TEL Technology Center - Albany (US)*
- 9:40 SURF2-O2-122 • Submillimetric patterns of organic/inorganic deposition
on low temperature substrates using a novel atmospheric pressure
plasma torch CVD
K. Acharya¹, S. Bulou¹, T. Gaulain¹, M. Gérard¹, G. Frache¹, P. Choquet¹
Luxembourg Institute of Science and Technology (LIST) - Esch-Sur-Alzette (LU)

10:00

COFFEE BREAK



Friday 27 September

10:30 – 12:30**PROC 3/3 Process control (including plasma diagnostics, plasma modelling)**

ANTIOPOLIS AUDITORIUM

Chair: P. Raynaud

- 10:30 **KEYNOTE // PROC3-K1-106** • Numerical modelling of DC magnetron discharges applied to Nb/Cu coatings in superconducting radio-frequency cavities

T. Richard¹, F. Avino¹, A. Grudiev¹, G. Rosaz¹, A. Sublet¹, M. Taborelli¹
¹CERN - Geneva (CH)

- 11:00 **PROC3-O2-135** • Model based analysis of the Ion Flux-Energy Distribution Functions in Capacitively Coupled Multi-Frequency Plasmas

E. Schüngel¹, A. Derzsi², M. Vass³, Z. Donkó³, J. Schulze⁴
¹Evatec AG - Trübbach (CH)

²Department of Physics, West Virginia University - Morgantown (US)

³Institute for Solid State Physics and Optics, Wigner Research Centre for Physics, Hungarian Academy of Sciences - Budapest (HU)

⁴Institute for Electrical Engineering, Ruhr-University-Bochum (DE)

- 11:20 **PROC3-O3-133** • The magnetic asymmetry effect: theoretical investigation by using a lumped element model

D. Engel¹, L. Kroll¹, M. Oberberg², J. Schulze², P. Awakowicz², R.P. Brinkmann¹

¹Institute of Theoretical Electrical Engineering, Ruhr University Bochum (DE)

²Institute of Electrical Engineering and Plasma Technology, Ruhr Univ. Bochum (DE)

- 11:40 **PROC3-O4-120** • Understanding the magnetron PECVD of DLC films in an acetylene admixture with a hybrid PICMC/DSMC model

A. Fauroux¹, A. Pflug², S. Lucas¹

¹University of Namur – NISM – LARN - Namur (BE)

²Fraunhofer Institute for Surface Engineering and Thin Films - Braunschweig (DE)

- 12:00 Closing ceremony

ANTIOPOLIS AUDITORIUM

14:00

SOCIAL PROGRAM

For registered person / 3 activities proposed:

- Option #1 - Excursion to Grasse, international capital of Flowers and Perfume
- Option #2 - Walking tour on the coastal path “sentier de Tire-Poil”
- Option #3 - Excursion to Saint Paul de Vence



Friday 27 September

10:30 – 12:30

NANO 3/3 Nanomaterials and nanostructured thin films

ELLA FITZGERALD ROOM

Chair: D. Lundin (provisional)

- 10:30 **KEYNOTE // NANO3-K1-069** • One step gold nanoparticles synthesis and deposition from an atmospheric pressure microwave PECVD – Applications to the fast and low cost production SERS substrates
S. Bulou¹, K. Baba¹, J.B. Chemin¹, P. Choquet¹, N. Boscher¹
Luxembourg Institute of Science and Technology - Esch-Sur-Alzette (LU)
- 11:00 NANO3-O2-009 • A tailored RF-ICP plasma to synthesize tailored nanoparticles
E. Haye¹, Y. Busby¹, M. Da Silva Pires¹, F. Bocchese¹, T. Hauet², C. Soon Chang², G. Dudek³, N. Job⁴, J. Ghanbaja², L. Houssiau¹, J.J. Pireaux¹
¹*Laboratoire Interdisciplinaire de Spectroscopie Electronique (LISE), Namur Institute of Structured Matter (NISM), University of Namur (BE)*
²*Institut Jean Lamour, UMR 7189, Université de Lorraine - Nancy (FR)*
³*Department of Physical Chemistry and Technology of Polymers, Faculty of Chemistry, Silesian University of Technology - Gliwice (PL)*
⁴*Department of Chemical Engineering – Nanomaterials, Catalysis, Electrochemistry, University of Liège - Liège (BE)*
- 11:20 NANO3-O3-097 • PtBi, PtCu and PtBiCu nanoclusters grown in a magnetron based gas aggregation source
A. Caillard¹, W. Chamorro-Coral¹, P. Brault¹, C. Coutanceau², S. Baranton²
¹*GREMI UMR7344, CNRS / Université d'Orléans (FR)*
²*IC2MP UMR 7285, CNRS / Université de Poitiers (FR)*
- 11:40 NANO3-O4-156 • Morphology dependent photocatalytic properties of ZnO nanostructures synthesized by plasma afterglow treatments
T. Gries¹, A. Imam¹, J. Ghanbaja¹, T. Belmonte¹
Institut Jean Lamour - CNRS - Université de Lorraine - Nancy (FR)

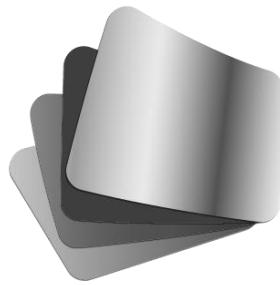
14:00

SOCIAL PROGRAM

For registered person / 3 activities proposed:

- Option #1 - Excursion to Grasse, international capital of Flowers and Perfume
- Option #2 - Walking tour on the coastal path “sentier de Tire-Poil”
- Option #3 - Excursion to Saint Paul de Vence





PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

POSTER PROGRAM

- **P1 / Session #1**
with exhibition cocktail
Tuesday 24 September
17:10 - 23:00
 - DEPO
 - GROM
 - HELI
 - INDU
 - LIQU
 - SURF
 - TRIB
- **P2 / Session #2**
with refreshments
Thursday 26 September
16:00 - 18:00
 - DEPO
 - GROM
 - LIQU
 - NANO
 - PROC
 - SOUR
 - TRIB



Poster session #1

▪ DEPO

DEPO -P1-011 Antifogging surfaces prepared from plasma copolymerization

F. Poncin-Epaillard¹, D. Debarnot¹, T.H. Tran¹

IMMM - Le Mans (FR)

DEPO -P1-034 A low-temperature (330 °C) deposition of high-performance thermochromic VO₂-based coatings for smart-window applications

T. Bártá¹, J. Vlcek¹, D. Kolenatý¹, J. Rezek¹, J. Houška¹, S. Haviar¹

University of West Bohemia - Pilsen (CZ)

DEPO -P1-038 Growing controllable-crystalline aluminium nitride thin films by plasma-enhanced atomic layer deposition at low temperature and its properties

T. Nguyen^{1,2}, N. Adjeroud¹, J. Guillot¹, J. Polesel¹

¹*Luxembourg Institute of Science and Technology - Esch-sur-Alzette (LU)*

²*University of LU - Esch-Sur-Alzette (LU)*

DEPO -P1-040 The role of atomic oxygen in the growth of single phase β-MnO₂ thin films by remote plasma assisted pulsed laser deposition

M. Tabbal¹, M. Abi Akl², W. Kassem¹, D. Haidar¹

¹*American University of Beirut - Beirut (LB)*

²*Texas A & M University at Qatar - Doha (QA)*

DEPO -P1-053 Water stability of organosilicon coatings prepared by atmospheric pressure plane-to-plane dielectric barrier discharge

L. Stafford¹, S. Babei¹, J. Profili¹, A. Dorris², S. Beck²,

S. Asadollahi³, A. Sarkissian³

¹*Université de Montréal - Montreal (CA)*

²*FPIInnovations - Pointe-Claire (CA)*

³*Plasmionique - Varennes (CA)*

DEPO -P1-063 Influence of the film thickness on the structure, optical and photocatalytic properties of TiO₂ thin films deposited by ICP-PECVD

W. Ravisy¹, D. Li¹, B. Dey², S. Bulou², P. Choquet², A. Goulet¹,

M. Richard-Plouet¹, A. Granier¹

¹*Institut des Matériaux Jean Rouxel (IMN), Université de Nantes, UMR*

CNRS 6502 - Nantes (FR)

²*Materials Research and Technology Department, LU Institute of Science and Technology - Esch-sur-Alzette (LU)*

DEPO -P1-074 Porous silicon double membranes for lithium- ion batteries

C. Yaddaden¹, N. Gabouze¹, M. Berouaken¹

CRTSE - El Harrach (DZ)



Poster session #1

- DEPO -P1-108 Effect of the silicon substrate nitridation on optical and electrical properties of silicon carbonitride thin films deposited by reactive magnetron sputtering
A. Bachar ¹, A. Bousquet ¹, C. Robert-Goumet ², G. Monier ²,
C. Varenne ², E. Tomasella ¹
¹*Université Clermont Auvergne, CNRS, SIGMA Clermont, ICCF - Clermont-Ferrand (FR)*
²*Université Clermont Auvergne, CNRS, SIGMA Clermont, Institut Pascal - Clermont-Ferrand (FR)*
- DEPO -P1-109 Hollow cathode plasma sputtering for coating the 90° elbow vacuum chambers of the ELENA antiproton ring at CERN
A. Sapountzis ¹, P. Costa Pinto ¹, T. Sinkovits ¹, A.M. Charlety ¹,
T. Richard ¹, G.J. Rosaz ¹, M. Taborelli ¹
CERN - Meyrin (CH)
- DEPO -P1-128 Pulsed Electron Cyclotron Wave Resonance Plasma Enhanced Chemical Vapour Deposition of photocatalytic TiO₂ thin films on polymeric substrates
B. Dey ¹, S. Bulou ¹, T. Gaulain ¹, W. Ravisy ², M. Richard-Plouet ²,
A. Gouillet ², A. Granier ², P. Choquet ¹
¹*Luxembourg Institute of Science and Technology - Esch Sur Alzette (LU)*
²*Institut des Matériaux Jean Rouxel - Nantes (FR)*
- DEPO -P1-145 Time resolved In situ characterization of deposited SiCN:H thin films obtained in Ar/TMS/N₂ dual ECR and RF-PVD by infrared absorption spectroscopy (FTIR)
Z. Al Hallak ^{1,2}, R. Hugon ¹, P. Pigeat ¹, A. Ahmad ², A. Naja ²,
M. Belmahi ¹
¹*Institut Jean Lamour UMR 7198, CNRS, Univ. de Lorraine - Nancy (FR)*
²*Laboratoire de Physique et Modélisation, Université LBaise - Tripoli (LB)*
- DEPO -P1-171 Oblique deposition of nickel thin films by HiPIMS
H. Hajihoseini ¹, S.P. Ingvarsson ¹, M. Kateb ¹, J.T. Gudmundsson ¹
Science Institute, University of Iceland - Reykjavik (IS)
- DEPO -P1-181 Organosilicon coatings deposited by cold nitrogen plasma post-discharge for prevention of biofilm formation in food and medical sectors
M. Hage ¹, B. Crocco ¹, S. Khelissa ¹, M. Abdallah ¹, H. Akoum ²,
N.E. Chihib ¹, C. Jama ¹
¹*Université de Lille - Lille (FR)*
²*Université LBaise - Saida (LB)*



Poster session #1

▪ GROM

GROM -P1-010 CrN thin film synthesis in Ar/N₂ and Ar/NH₃, a comparative study
E. Haye¹, L. Rassinfosse¹, J.L. Colaux², N. Tumanov³,
J.J. Pireaux¹, S. Lucas²

¹Laboratoire Interdisciplinaire de Spectroscopie Electronique (LISE), Namur Institute of Structured Matter (NISM), University of Namur (BE)

²Laboratoire d'Analyse par Réactions Nucléaires (LARN), Namur Institute of Structured Matter (NISM), University of Namur (BE)

³Chemistry Department, University of Namur (BE)

GROM -P1-044 Reactivity to organic vapors at PECVD PDMS-like surfaces for gas detection and membrane separation

G. Dakroub¹, T. Duguet², C. Lacaze-Dufaure², S. Roualdès³,
V. Rouessac³

¹IEM & CIRIMAT - Montpellier (FR)

²CIRIMAT - Toulouse (FR)

³IEM - Montpellier (FR)

GROM -P1-083 Prediction of the column tilt angle in GLAD by sputtering

A. Besnard¹

Arts et Metiers ParisTech – LaBoMaP - Cluny (FR)

GROM -P1-084 Low pressure plasma polymerization of cyclopropylamine in a hollow cathode reactor

S. Lucas¹, S. Mathioudaki¹, C. Vandenabeele¹, A. Pflug²

¹University of Namur, LARN-NISM - Namur (BE)

²Fraunhofer Institute for Surface Engineering and Thin Films IST - Braunschweig (DE)

GROM -P1-086 PVD large scale growth simulation: Influence of the substrate roughness

A. Besnard¹, S. Lucas², P. Moskovkin²

¹Arts et Metiers ParisTech – LaBoMaP - Cluny (FR)

²University of Namur- LARN-NISM - Namur (BE)

GROM -P1-098 Preparation of DLC films by microwave plasma-assisted chemical vapour deposition in open-air

H. Yagi¹, S. Yudate¹

Ehime University - Matsuyama (JP)

GROM -P1-114 Bio-inspired functional coatings on plasma-processed polymeric materials for vehicular interiors

H. Salapare¹, C. Fradin¹, A. Sathanikan¹, T. Darmanin¹,

S. Amigoni¹, A. Zenerino¹, F. Guittard¹

Université Côte d'Azur, NIce Lab, IMREDD - Nice (FR)



Poster session #1

▪ HELI

- HELI -P1-085 Surface functionalisation, nanoroughness and drug delivery by atmospheric plasma jet on scaffolds
A. Patelli ¹, F. Mussano ², P. Brun ¹, T. Genova ², E. Ambrosi ³, N. Michieli ¹, G. Mattei ¹, P. Scopece ⁴, L. Moroni ⁵
¹*University of Padova - Padova (IT)*
²*University of Torino - Torino (IT)*
³*University of Venezia - Venezia (IT)*
⁴*Nadir srl - Venezia (IT)*
⁵*University of Maastricht - Maastricht (NL)*

▪ INDU

- INDU -P1-020 Titanium nitrides coating for hard chromium replacement
M. Cavarroc ¹, B. Giroire ², L. Teulé-Gay ², D. Michau ², A. Poulon-Quintin ²
¹*Safran Tech, Materials & Processes dep. - Magny-les-Hameaux (FR)*
²*ICMCB - Pessac (FR)*
- INDU -P1-136 Atom probe tomography analysis for additive manufacturing
T. Prosa ¹, P. Clifton ¹, R. Katherine ¹, C. Yimeng ¹, U. Robert ¹, L. David ¹, B. Anna ²
¹*Cameca Instruments Inc. - Fitchburg (US)*
²*Cameca Instruments Inc. - Gennevilliers (FR)*
- INDU -P1-188 From component to system for a faster technology
A. Vasiliu ¹
COMET - Flamatt (CH)

▪ LIQU

- LIQU -P1-049 Study of the synthesis of nanoparticles in liquid phase enhanced by microsecond plasma discharges at atmospheric pressure
S. Cuynet ¹, C. Edbaeich ¹, M. Mazri ¹, C. Noel ¹, L. De Poucques ¹, G. Henrion ¹, T. Belmonte ¹
Institut Jean Lamour - Nancy (FR)

▪ SURF

- SURF -P1-043 Physicochemical modification of spin-coated TiO₂ nanoparticle thin film by ICP low pressure oxygen plasma
M. Mitronika ¹, J. Profili ², W. Ravisy ³, A. Goulet ³, L. Stafford ², A. Granier ³, M. Richard-Plouet ³
¹*IMN, Université de Nantes, CNRS - Nantes (FR)*
²*Dép. de Physique, Université de Montréal, Québec - Montréal (CA)*
³*IMN, Université de Nantes, CNRS - Nantes (FR)*
- SURF -P1-051 Functionalization and characterization study of Metal Organic Frameworks (MOF) by plasma process
A. Najah ¹, S. Cuynet ¹, G. Henrion ¹, D. Boivin ¹, L. De Poucques ¹, T. Belmonte ¹, V. Fierro ¹
Institut Jean Lamour, Université de lorraine, CNRS - Nancy (FR)

Poster session #1

- SURF -P1-055 The role of SiF₄ physisorption in silicon cryoetching
T. Tillocher¹, G. Antoun¹, P. Lefaucheux¹, R. Dussart¹,
C. Cardinaud², A. Girard², S. Tahara³, K. Yamazaki⁴,
K. Yatsuda⁴, J. Faguet⁵, K. Maekawa⁵
¹*GREMI, Université d'Orléans - CNRS - Orléans (FR)*
²*IMN, Université de Nantes - CNRS - Nantes (FR)*
³*Tokyo Electron Limited Miyagi - Miyagi (JP)*
⁴*Tokyo Electron Limited - Tokyo (JP)*
⁵*TEL Technology Center America - Albany (US)*
- SURF -P1-082 Measuring the energy flux at the substrate during plasma based deposition techniques: a way to investigate both the sputtering process and the film growth
A-L. Thomann¹, R. Graillot-Vuillecot¹, S. Konstantinidis²,
T. Lecas¹, A. Caillard¹
¹*GREMI CNRS/Université d'Orléans - Orléans (FR)*
²*ChIPS université de Mons - Mons (BE)*
- SURF -P1-146 Study of interactions between a PMMA support and cold plasma used for thin film deposition
M. Kouicem¹, E. Tomasella², A. Bousquet², G. Monier³,
C. Robert-Goumet³, L. Dubost¹
¹*IREIS/HEF Groupe, Large Area Coatings Department - Andrézieux (FR)*
²*Univ. Clermont Auvergne, CNRS, SIGMA Clermont, ICCF - Aubière (FR)*
³*Univ. Clermont Auvergne, CNRS, Institut Pascal - Aubière (FR)*
- SURF -P1-148 Etching of Ge-Sb-Se glasses in SF₆ and SF₆/Ar plasma
T. Meyer¹, A. Girard¹, C. Cardinaud¹, V. Nazabal², P. Nemec³
¹*IMN, UMR-CNRS 6502, Université de Nantes (FR)*
²*Institut des Sciences Chimiques de Rennes, UMR-CNRS 6226, Université de Rennes 1 (FR)*
³*Department of Graphic Arts and Photophysics, Faculty of Chemical Technology, University of Pardubice (CZ)*
- SURF -P1-150 Physicochemical modification of spin-coated silver nanoparticle thin film by atmospheric surface-wave microwave post-discharge
J. Trahan¹, J. Profili¹, M. Mitronika², A. Goulet², A. Granier²,
M. Richard-Ploet², L. Stafford¹
¹*Université de Montréal - Montréal (CA)*
²*Institut des Matériaux Jean Rouxel - Nantes (FR)*
- SURF -P1-159 Patterning at micrometric scale of metallic surfaces by plasma etching
F. Laourine^{1,2}, G. Marcos¹, S. Guilet², T. Czerwiec¹
¹*Institut Jean Lamour - Nancy (FR)*
²*Centre de Nanosciences et de nanotechnologies - Paris (FR)*



Poster session #1

▪ TRIB

- TRIB -P1-015 Optimization of Mo-S-N solid lubricant films with improved adhesion and low friction by DC magnetron sputtering
K. Hebbar Kannur¹, C. Pupier², C. Heau², A. Cavaleiro³
¹IRES-HEF group, University of Coimbra - Andrézieux-Bouthéon (FR)
²IRES-HEF group - Andrézieux-Bouthéon (FR)
³University of Coimbra (PT)
- TRIB -P1-030 Characterization of duplex, nanocomposite and nanolayered thin films
B. Skoric¹, A. Miletic², P. Terek², L. Kovacevic²
¹Prof. Phd - Novi Sad (RS)
²Ass.Prof. Phd - Novi Sad (RS)
- TRIB -P1-068 Study of Cr, CrN, CrAlN monolayers and Cr/CrN/CrAlN multilayers developed by DC magnetron sputtering for mechanical application
C. Nouveau¹, K. Aouadi², A. Besnard¹, B. Tili³, M. Chafra²
¹Arts et Metiers ParisTech - Cluny (FR)
²Ecole Polytechnique de Tunisie - La Marsa (TN)
³Ecole Nationale d'Ingénieurs de Tunis - Tunis (TN)
- TRIB -P1-080 Tribological behavior of ZrN/Ta Coatings Deposited by RF Magnetron Sputtering on Ti-6Al-4V and CoCrMo Alloys
C. Ramoul^{1,2}, C. Nouveau³, N. Beliardouh¹, H. Kaleli⁴
¹Université BADJI Mokhtar - Annaba (DZ)
²Centre de Recherche en Technologies Industrielles CRTI - Alger (DZ)
³Arts et Metiers ParisTech - Cluny (FR)
⁴Yildiz Technical University - Istanbul (TR)
- TRIB -P1-103 Reactive HiPIMS deposition of Ti-Al-N: Influencing the Cubic to Wurtzite phase transition
L. Zauner¹, L. Zauner², T. Wojcik³, T. Kozák⁴, J. Capek⁴,
H. Bolvardi⁵, S. Kolozsvári⁶, P.H. Mayrhofer¹, P.H. Mayrhofer²,
H. Riedl², H. Riedl³
¹Christian Doppler Laboratory for Application Oriented Coating Development at the Institute of Materials Science and Technology, TU Wien (AT)
²Christian Doppler Laboratory for Surface Engineering of high-performance Components, TU Wien (AT)
³Institute of Materials Science and Technology, TU Wien (AT)
⁴Dep. of Physics and NTIS, European Center of Excellence, University of West Bohemia - Plzen (CZ)
⁵Oerlikon Balzers, Oerlikon Surface Solutions AG (LI)
⁶Plansee Composite Materials GmbH, DE - Lechbruck (DE)
- TRIB -P1-186 Deposition and characterization of multilayer CrAlN/CrAlO_x coatings deposited by CAE-PVD
E. Almandoz¹, J. F. De Ara¹, J. Martínez De Bujanda¹,
J.F. Palacio¹, G. Alcalá², J.A. García³, G.G. Fuentes⁴,
R.J. Rodríguez Trías³
¹AIN - Cordovilla (ES)
²UCM - Madrid (ES)
³UPNA - Pamplona (ES)
⁴AIN - Pamplona (ES)

Poster session #2

▪ DEPO

DEPO -P2-004 Effect of RF sputtering deposition parameters on silicon nitride coatings

S. Meziani¹

Centre de Recherche en Technologie des Semiconducteurs pour l'Energétique - Algiers (DZ)

DEPO -P2-029 Superhydrophobic plasma polymerization on surfaces from smooth to laser textured multi-scale structure

R. Elleb¹, F. Mermet², T. Engel³, G. Chabrol⁴,
F. Poncin-Epaillard¹

¹IMMM - Université du Maine - Le Mans (FR)

²IRePA LASER - Illkirch-Graffenstaden (FR)

³INSA Strasbourg (FR)

⁴IPPC, ICUBE - Illkirch-Graffenstaden (FR)

DEPO -P2-045 Optimization of gold coatings for bipolar plates of polymer electrolyte membrane fuel cells

M-A. Leroy¹, H. Sauzet¹, C. Heau¹, Y. Gachon¹
IREIS / Groupe HEF - Andrézieux Bouthéon (FR)

DEPO -P2-046 Determination the structure of ZnSnN₂ thin films by using transmission electron microscopy

F. Alnjiman^{1,2}, S. Bruyère¹, J. Ghanbaja¹, S. Diliberto¹,
P. Boulet¹, H. Albrithen², P. Miska¹, J.F. Pierson¹

¹Institut Jean Lamour, Université de Lorraine, Nancy, FR - Nancy (FR)

²Department of Physics and Astronomy at College of Science, King Saud University at Riyadh - Riyadh (SA)

DEPO -P2-052 High temperature stable ZrN-based thin films for plasmonic applications

J-F. Pierson¹, M. Gipperich¹, D. Pilloud¹, T. Easwarakhanthan¹,
H. Rinnert¹
Institut Jean Lamour (UMR CNRS 7198) – Univ. de Lorraine - Nancy (FR)

DEPO -P2-054 Evidence of in-depth transport phenomena during deposition of hydrophobic organosilicon coatings on porous cellulosic materials in atmospheric pressure dielectric barrier discharges

L. Stafford¹, J. Profili¹, S. Babei¹, A. Dorris², S. Beck²,
S. Asadollahi³, A. Sarkissian³

¹Université de Montréal - Montréal (CA)

²FPIInnovations - Pointe-Claire (CA)

³Plasmionique - Varennes (CA)

DEPO -P2-119 Plasma-based deposition of coatings for Drop Coating Deposition Raman (DCDR) Spectroscopy

A. Kuzminova¹, M. Procházka¹, E. Kocišová¹, O. Kylián¹
Charles University, Faculty of Mathematics and Physics - Praha (CZ)



Poster session #2

- DEPO -P2-163 Tuning the localized surface plasmon resonances of micro-triangular patterns
A. Bercea¹, C. Constantinescu ¹, F. Dumas-Bouchiat ¹,
C. Champeaux ¹
University of Limoges, CNRS, IRCEP, UMR7315 - Limoges (FR)
- DEPO -P2-178 Plasma-Enhanced Pulsed Laser Deposition of metal-oxide thin films
E. Wagenaars¹, D. Meehan ¹, S. Rajendiran ¹, A. Rossall ²
¹*York Plasma Institute, Department of Physics, University of York (UK)*
²*School of Computing & Engineering, University of Huddersfield (UK)*
- DEPO -P2-180 Structure, stress and physical properties of Mo-Al-N thin films deposited by reactive magnetron sputtering
G. Abadias¹, F. Angay ¹, D. Eyidi ¹, S. Camelio ¹
Institut Pprime, CNRS-Univ. de Poitiers - Futuroscope-Chasseneuil (FR)

▪ GROM

- GROM -P2-177 The role of each cathode in GLAD dual mode. Experimental and numerical investigations
A. Besnard^{1,2}, E. Haye ³, J. Colaux ⁴, J. Muller ², J.J. Pireaux ³,
S. Lucas ³
¹*Arts et Métiers ParisTech, LaBoMaP - Cluny (FR)*
²*University of Namur, LARN-NISM - Namur (BE)*
³*University of Namur, LISE-NISM - Namur (BE)*
⁴*University of Namur, SIAM - Namur (BE)*

▪ LIQU

- LIQU -P2-174 Dressed dust acoustic soliton energy in dusty space plasmas
R. Amour¹, M. Benzekka ²
¹*Plasma Physics Group, Theoretical Physics Laboratory, Faculty of Physics, University of Bab-Ezzouar, USTHB - Bab Ezzouar (DZ)*
²*Laboratoire de Physique des Particules et Physique Statistique, ENS-Kouba - Algiers (DZ)*
- LIQU -P2-175 Nonlinear localized dust acoustic waves in dusty plasma with nonthermal ions featuring Gurevich distribution
M. Ouazene¹, R. Amour ²
¹*Plasma Physics Group, Theoretical Physics Laboratory, Faculty of Physics, University of Bab-Ezzouar, USTHB - Bab Ezzouar (DZ)*
²*Plasma Physics Group, Theoretical Physics Laboratory, Faculty of Physics, University of Bab- Ezzouar, USTHB - Bab Ezzouar (DZ)*
- LIQU -P2-176 Nonlinear structures in dusty space plasma in the presence of polarization force
M. Benzekka^{1, 2}, R. Amour ¹, T.H. Zerguini ¹
¹*Plasma Physics Group, Theoretical Physics Laboratory, Faculty of Physics, University of Bab-Ezzouar, USTHB - Algiers (DZ)*
²*Département de physique, Ecole Normale Supérieure (ENS), Kouba - Algiers (DZ)*



Poster session #2

▪ NANO

NANO -P2-032 Dependence of plasma polymer / metal composite structure on the nature of metallic nanoparticles

D. Debarnot¹, A. Mansour¹, F. Poncin-Epaillard¹
Le Mans Université - Le Mans (FR)

NANO -P2-118 Femtosecond laser nanostructuring of magnetron sputtered functional oxide thin films

M. Tabbal¹, A. Talbi², P. Coddet², M. Mickan², A.L. Thomann², E. Millon², A. Stoltz², C. Boulmer-Leborgne², G. O'connor³, N. Semmar²

¹American University of Beirut - Beirut (LB)

²GREMI-Universite d'Orleans - Orleans (FR)

³National University of Ireland - Galway (IE)

NANO -P2-182 Study of the interactions between a resonant power supply and a flat dielectric barrier discharge lamp

B. Caillier¹, N. Hamza², D. Florez³, H. Piquet²

¹Laboratoire Diagnostics des Plasmas Hors Equilibre (DPHE), Université de Toulouse, INU Champollion - Albi (FR)

²LAPLACE, Université de Toulouse, CNRS, INPT, UPS - Toulouse (FR)

³Universidad Sergio Arboleda - Bogota (CO)

NANO -P2-183 Atmospheric plasma-assisted modification of LiYF₄:Eu³⁺

B. Caillier¹, P. Guillot¹, J.M. Gonçalves², J.M.A. Cajut²

¹Laboratoire Diagnostics des Plasmas Hors Equilibre (DPHE), Université de Toulouse, INU Champollion - Albi (FR)

²Department of Chemistry – FFCLRP, University of Sao Paulo - Ribeirao Preto, Sp (BR)

▪ PROC

PROC -P2-035 Characterization of transport of neutral and ionized species in reactive HiPIMS process

D. Boivin¹, A. El Farsy¹, A. Najah¹, S. Cuynet¹, C. Noel¹, T. Belmonte¹, L. De Poucques¹
Université de Lorraine, CNRS, IJL, F-54000, FR - Nancy (FR)

PROC -P2-056 Influence of N₂, O₂, and H₂ admixtures on the electron power balance and neutral gas heating in microwave Ar plasmas at atmospheric pressure

A. Durocher-Jean¹, N. Delnour¹, L. Stafford¹
Universite de Montreal - Montreal (CA)



Poster session #2

- PROC -P2-087 Statistical evaluation of late and early afterglow coefficients in the flowing afterglow of microwave nitrogen plasmas
G. Robert Bigras¹, A. D'arco¹, L. Stafford¹
Université de Montréal - Montréal (CA)
- PROC -P2-134 Characterization of an assisting plasma source in reactive sputter deposition processes
E. Schüngel¹, S. Gees¹, S. Schwyn Thöny¹
Evatec AG - Trübbach (CH)
- PROC -P2-139 Modelling of High-power impulse magnetron sputtering of Ar/O₂ mixture using global kinetic model.
J. Zgheib¹
Institut des matériaux Jean Rouxel (IMN) - Nantes (FR)
- PROC -P2-160 Ammonia production in low pressure H₂-N₂ DECR plasmas
C. Noel¹, A. Maizeray¹, G. Marcos¹, T. Czerwiec¹
Institut Jean Lamour - Nancy (FR)
- PROC -P2-185 Movement of titanium ions in the target region of HiPIMS
J. Held¹, A. Von Keudell¹, V. Schulz-Von Der Gathen¹
Experimental Physics II, Ruhr University Bochum - Bochum (DE)
- PROC -P2-187 Study of particle transport above the target in high power impulse magnetron sputtering plasmas using a marker technique
S. Thiemann-Monjé¹, J. Held¹, M. Sackers¹, A. Von Keudell¹
Ruhr-University Bochum (DE)

▪ SOUR

- SOUR -P2-019 Pressure and voltage effects on UV efficacy in a mercury-free neon-xenon dielectric barrier discharge
F. Haddou¹, P. Guillot¹, A. Belasri², B. Caillier¹
¹*Laboratoire Diagnostics des Plasmas Hors Équilibre (DPHE), Université de Toulouse, INU Champollion - Albi (FR)*
²*Laboratoire de Physique des Plasmas, Matériaux Conducteurs et leurs Applications (LPPMCA), Université des Sciences et de la Technologie (USTO-MB) - Oran (DZ)*
- SOUR -P2-064 Microwave plasma source development for the study of ionization processes influence on isotopic fractionation of nitrogen and hydrogen
L. Pentecoste-Cuynet¹, L. Tissandier¹, D. Bekaert¹, L. Piani¹, T. Rigaudier¹, D. Lequin¹, B. Marty¹
Centre de Recherche Pétrographique et Géochimique, UMR 7358 - CNRS/Université de Lorraine - Vandoeuvre Les Nancy (FR)



Poster session #2

SOUR -P2-099 Combinatorial investigation of high entropy alloy systems sputtered by highly energized ion beams

L. Petho¹, G. Roussely², P. Nagy¹, T. Nelis³, P. Sortais²,
J. Michler¹

¹*Lab. for Mechanics of Materials and Nanostructures, Empa - Thun (CH)*

²*Polygon Physics - Grenoble (FR)*

³*Institute ALPS, Berner Fachhochschule - Biel (CH)*

SOUR -P2-107 Arc sources for low defect coatings and high target utilisation

B. Kurian¹, V. Bellido-Gonzalez¹, D. Monaghan,¹ B. Daniel¹,
R. Brown¹, J. Price¹, A. Azzopardi¹, T. Sgrilli¹,
O. Hernandez-Rodriguez¹

Gencoia Ltd - Liverpool (UK)

SOUR -P2-126 Characterization of magnetron sputtering discharges during the formation and transport of metal nanoparticles

A. Chami¹, C. Arnas¹, L. Couëdel²

¹*Aix-Marseille université - Marseille (FR)*

²*University of Saskatchewan - Saskatoon (CA)*

SOUR -P2-143 Multi microwave microplasmas generated in capillaries for laser application

O. Leroy¹, S. Latchabady¹, J. Robert¹, T. Minea¹
LPGP - CNRS - Orsay (FR)

SOUR -P2-151 Insight on the discharge parameters in magnetron sputtering by a 2D PIC-MCC modeling

A. Revel¹, L. De Poucques², T. Minea¹

¹*Laboratoire de Physique des Gaz et des Plasmas, CNRS UMR 8578,*

Université Paris-Sud, Université Paris-Saclay - Orsay (FR)

²*Institut Jean Lamour UMR 7198, CNRS – Univ. de Lorraine - Nancy (FR)*

▪ TRIB

TRIB -P2-075 New generation of duplex treatments on pure Fe substrates

D. Cotton¹, C. Nouveau¹, N. Bentayeb¹, A. Besnard¹
Arts et Métiers ParisTech - Cluny (FR)

TRIB -P2-149 Influence of titanium addition on the phase composition and properties of tungsten borides thin films

T. Moscicki¹, R. Psiuk¹, H. Slominska¹

Institute of Fundamental Technological Research Polish Academy of Science - Warsaw (PL)

TRIB -P2-155 Elaboration of MAX phases in TiAl alloys by plasma-assisted diffusion treatments

T. Czerwiec¹, J. Kadoc¹, A. Trigui¹, E. Guillaume²,
M. Grégory¹, D. Jacky¹

¹*Institut Jean Lamour (IJL) - Nancy (FR)*

²*Critt metal 2T - Nancy (FR)*

AUTHORS INDEX

A			
Abadias G.	DEPO -P2-180 NANO1-O2-076 PLATH00173	Arnas C.	SOUR -P2-126
Abdallah M.	DEPO -P1-181	Asadollahi S.	DEPO -P1-053 DEPO -P2-054
Abessolo Ondo D.	DEPO4-O2-022	Assie B.	DEPO4-O3-096
Abi Akl M.	DEPO -P1-040	Aubert X.	PROC1-O2-115
Achard J.	TRIB5-O1-113	Avino F.	DEPO1-O5-061 PROC3-K1-106
Acharya K.	SURF2-O2-122	Awakowicz P.	GROM2-O3-125 PROC3-O3-133
Adams P.	DEPO1-O2-025	Azens A.	NANO1-O5-110
Adjeroud N.	DEPO -P1-038	Azzopardi A.	SOUR -P2-107
Adzhani S.	PROC2-O1-071	B	
Ahmad A.	DEPO -P1-145	Baba K.	NANO3-K1-069
Akoum H.	DEPO -P1-181	Babei S.	DEPO -P1-053 DEPO -P2-054
Al Hallak Z.	DEPO -P1-145	Babonneau D.	NANO1-O2-076
Albritthen H.	DEPO -P2-046	Bacakova L.	HELI1-O1-124
Alcalá G.	TRIB -P1-186	Bachar A.	DEPO -P1-108
Allard C.	SURF1-O1-070	Balalykin N.I.	NANO2-O5-101
Almandoz E.	TRIB -P1-186	Baranton S.	NANO3-O3-097
Alnjiman F.	DEPO -P2-046	Bardin I.V.	LIQU1-O1-042
Alvarez R.	GROM2-K1-130	Bardon J.	TRIB4-O2-058
Amberg M.	DEPO2-K1-024	Barnabe A.	DEPO4-O5-168
Ambrosi E.	HELI -P1-085	Barrie J.	DEPO1-O2-025
Amigoni S.	GROM -P1-114	Bárta T.	DEPO -P1-034
Amour R.	LIQU -P2-174 LIQU -P2-175 LIQU -P2-176	Bauville G.	HELI1-O2-161
Anders A.	DEPO5-O4-037	Béchu S.	PROC1-O2-115
Angay F.	DEPO -P2-180	Beck S.	DEPO -P1-053 DEPO -P2-054
Anna B.	INDU -P1-136	Bedo T.	DEPO1-O4-014
Antoun G.	SURF2-O1-026 SURF -P1-055	Bekaert D.	SOUR -P2-064
Aouadi K.	TRIB -P1-068	Belasri A.	SOUR -P2-019
Arnalds U.B.	DEPO5-O3-162	Beliardouh N.	TRIB -P1-080



Bellido-Gonzalez V.	PROC1-O4-050 SOUR -P2-107	Boscher N.D.	NANO3-K1-069 DEPO4-O2-022
Belmahi M.	DEPO -P1-145	Boulet P.	DEPO -P2-046
Belmonte T.	LIQU -P1-049 NANO3-O4-156 PROC -P2-035 SURF -P1-051	Boulmer-Leborgne C. Bousquet A.	NANO -P2-118 DEPO1-O1-023 DEPO -P1-108 SURF -P1-146
Ben Hadj Mabrouk A.	DEPO4-O3-096	Bousser E.	INDU1-O5-021
Bénédic F.	TRIB5-O1-113	Boyer R.	NANO2-O4-165
	PROC1-O2-115	Brault P.	LIQU1-O2-123
Bentayeb N.	TRIB -P2-075	Brenning N.	NANO3-O3-097
Benyahia L.	DEPO3-O3-088	Brindley J.	PROC1-O1-142
Benzekka M.	LIQU -P2-174 LIQU -P2-176	Brinkmann R.P.	PROC1-O4-050 PROC3-O3-133
Bercea A.	DEPO -P2-163	Brinza O.	TRIB5-O1-113
Bergeron F.	INDU1-O5-021	Britun N.	NANO1-O3-095
Berouaken M.	DEPO -P1-074		PROC1-O3-067 PROC2-O1-071
Berthomé G.	TRIB3-O2-144		SOUR1-O2-072
Bès A.	PROC1-O2-115 PROC2-O3-131	Brown R.	SOUR -P2-107
Besnard A.	GROM1-O3-081 GROM -P1-083 GROM -P1-086 GROM -P2-177 TRIB1-O2-060 TRIB -P1-068 TRIB -P2-075	Brühl S. Brun P. Bruyère S. Bui A.	TRIB1-O1-005 HELI -P1-085 DEPO -P2-046 DEPO1-O3-048 GROM1-O2-036 INDU1-O1-190
Biederman H.	NANO2-O2-105	Bulou S.	DEPO -P1-063 DEPO3-O2-127
Bigan M.	DEPO3-O5-140		DEPO -P1-128
Bigarre J.	LIQU1-O2-123		GROM2-O2-062
Blahová L.	HELI1-O1-124		NANO3-K1-069 SURF2-O2-122
Bocchese F.	NANO3-O2-009	Bursikova V.	TRIB2-K1-065
Boivin D.	PROC -P2-035 SURF -P1-051	Busby Y. Butler A.	NANO3-O2-009 PROC1-O1-142
Bolvardi H.	TRIB -P1-103		
Bonnet P.	DEPO1-O1-023		
Borges J.	DEPO1-O4-014		
Borroto A.	GROM1-O2-036		



C			
Cabo A.	TRIB1-O1-005	Champeaux C.	DEPO -P2-163 DEPO4-O4-166 NANO2-O4-165
Cachoncinlle C.	GROM1-O1-007	Chapon P.	DEPO3-O1-102
Cacot L.	PROC2-O5-121	Charlety A.M.	DEPO1-O5-061
Cada M.	PROC2-O2-066 PROC2-O4-169	Chazelas C.	DEPO -P1-109 DEPO3-O4-100
Caillard A.	DEPO5-K1-116 GROM1-O1-007 LIQU1-O2-123 NANO3-O3-097 SURF -P1-082	Chemin J.B. Chen Y. Chihib N.E. Choquet P.	NANO3-K1-069 INDU1-O1-190 DEPO -P1-181 DEPO -P1-063 DEPO3-O2-127 DEPO -P1-128 GROM2-O2-062
Caillier B.	NANO -P2-183 SOUR -P2-019 NANO -P2-182		NANO3-K1-069 SURF2-O2-122
Cairney J.	TRIB1-O3-158		
Caiut J.M.A.	NANO -P2-183	Chu C.T.	DEPO1-O2-025
Calatroni S.	DEPO1-O5-061	Clergereaux R.	PROC2-O5-121 TRIB4-O2-058
Camelio S.	DEPO -P2-180 NANO1-O2-076	Clifton P.H.	INDU -P1-136 INDU1-O1-190
Canal C.	PLATH00189	Coddet P.	DEPO5-K1-116 NANO -P2-118
Capek J.	DEPO5-O2-057 PROC2-O2-066 TRIB -P1-103	Colaux J.L.	GROM -P2-177 GROM -P1-010
Capon F.	DEPO1-O3-048	Constantinescu C.	DEPO -P2-163
Car R.	NANO1-K1-093	Costa D.	DEPO1-O4-014
Cardinaud C.	SURF -P1-055 SURF -P1-148	Costa Pinto P.	DEPO -P1-109
Carling-Plaza A.	DEPO2-O2-016	Coto B.	TRIB2-O3-111
Carnide G.	TRIB4-O2-058	Cotton D.	TRIB -P2-075
Cattaruzza E.	SOUR1-O1-059	Couëdel L.	SOUR -P2-126
Cavaleiro A.	TRIB -P1-015	Coulibaly M.	TRIB5-O2-141
Cavarroc M.	INDU -P1-020 INDU1-O5-021	Coutanceau C.	NANO3-O3-097
Cernochova P.	HELI1-O1-124	Cristea D.	DEPO1-O4-014
Chabrol G.	DEPO -P2-029	Crocco B.	DEPO -P1-181
Chafra M.	TRIB -P1-068	Cuynet S.	LIQU -P1-049 LIQU1-O2-123
Chami A.	SOUR -P2-126		PROC -P2-035
Chamorro-Coral W.	NANO3-O3-097		SURF -P1-051



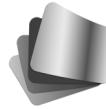
Cvelbar U.	SURF1-O2-154	Dorris A.	DEPO -P1-053
Czerwiec T.	PROC -P2-160 SURF -P1-159 TRIB5-O2-141 TRIB -P2-155	Dublanche-Tixier C.	DEPO3-O4-100
		Dubost L.	SURF -P1-146
		Dudek G.	NANO3-O2-009
		Duguet T.	GROM -P1-044
		Dumas-Bouchiat F.	DEPO -P2-163
			DEPO4-O4-166
			NANO2-O4-165
D			
Da Silva Pires M.	NANO3-O2-009	Durocher-Jean A.	PROC -P2-056
D'agosto F.	DEPO4-O3-096	Dussart R.	SURF2-O1-026
Dakroub G.	GROM -P1-044		SURF -P1-055
Dalibón E.L.	TRIB1-O1-005		
Damman P.	NANO2-O3-132		
Daniel B.	PROC1-O4-050 SOUR -P2-107		
D'arco A.	PROC -P2-087	E	
Darmanin T.	GROM -P1-114	Easwarakhanthan T.	DEPO -P2-052
David L.	INDU -P1-136	Edbaeich C.	LIQU -P1-049
De Los Arcos T.	GROM2-O3-125	Eichenhofer G.	INDU1-O3-167
De Poucques L.	LIQU -P1-049 PROC -P2-035 SOUR -P2-151 SURF -P1-051	El Farsy A.	PROC -P2-035
Debarnot D.	DEPO -P1-011 NANO -P2-032	El Shaer M.	LIQU1-O3-031
Dekkar D.	TRIB5-O1-113 PROC1-O2-115	Eldaly M.	LIQU1-O3-031
Delnour N.	PROC -P2-056	Elias M.	NANO1-O2-092
Dempsey N.	DEPO4-O4-166	Elleb R.	DEPO -P2-029
Derzsi A.	PROC3-O2-135	Engel T.	DEPO -P2-029
Dey B.	DEPO -P1-063 DEPO3-O2-127 DEPO -P1-128 GROM2-O2-062	Engel D.	PROC3-O3-133
Desecot S.	TRIB1-O2-060	Esparza Contro C.	TRIB3-O2-144
Diab H.	LIQU1-O3-031	Evrard M.	GROM1-O3-081
Diliberto S.	DEPO -P2-046	Eyidi D.	DEPO -P2-180
Diop A.	DEPO2-O2-016	G. Ezo'o	TRIB -P2-155
Donkó Z.	PROC3-O2-135		
		F	
		F. De Ara J.	TRIB -P1-186
		Fafin A.	NANO1-O2-076
		Faguet J.	SURF2-O1-026
			SURF -P1-055
		Falentin-Daudré C.	TRIB5-O1-113
		Fauroux A.	PROC3-O4-120



Fekete M.	TRIB2-K1-065	Girard A.	SURF -P1-055
Fenker M.	DEPO4-K1-039	Girard P.M.	SURF -P1-148
Fierro V.	SURF -P1-051	Giroire B.	HELI1-O2-161
Filipic G.	SURF1-O2-154	Glad X.	INDU -P1-020
Fleury M.	HELI1-O2-161	Gonçalves J.M.	SURF1-O1-070
Florez D.	NANO -P2-182	Goullet A.	NANO -P2-183
Folgner K.	DEPO1-O2-025		DEPO -P1-063
Frache G.	SURF2-O2-122		DEPO3-O2-127
Fradin C.	GROM -P1-114		DEPO -P1-128
Fuentes G.G.	TRIB -P1-186		GROM2-O2-062
			NANO2-O1-041
			SURF -P1-043
			SURF -P1-150

G

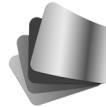
Gabor C.	DEPO1-O4-014	Graillot Vuillecot R.	GROM1-O1-007
Gabouze N.	DEPO -P1-074	Granier A.	SURF -P1-082
Gachon Y.	DEPO -P2-045		DEPO -P1-063
	TRIB3-O1-129		DEPO3-O2-127
Gadow R.	TRIB2-O2-013		DEPO -P1-128
Gaedike B.	TRIB2-O2-013		GROM2-O2-062
Gaiaschi S.	DEPO3-O1-102	Gries T.	NANO2-O1-041
Gaiser S.	GROM2-O4-012		SURF -P1-043
García J.A.	TRIB -P1-186		SURF -P1-150
García Wong A.C.	DEPO1-O3-048	Grosjean A.	DEPO2-O2-016
	GROM1-O2-036	Grudiev A.	DEPO1-O5-061
Gaudin M.	NANO2-O4-165	Grundmeier G.	PROC3-K1-106
Gaulain T.	DEPO3-O2-127	Gudmundsson J.T.	GROM2-O3-125
	DEPO -P1-128		DEPO -P1-171
	SURF2-O2-122		PROC1-O1-142
			PROC2-O4-169
Gautier N.	GROM2-O2-062	Guilet S.	SURF -P1-159
Gazeli K.	HELI1-O2-161	Guillot P.	NANO -P2-183
Gees S.	DEPO2-O3-078	Guillot J.	SOUR -P2-019
	PROC -P2-134		DEPO -P1-038
Genova T.	HELI -P1-085	Guittard F.	GROM -P1-114
Gérard M.	SURF2-O2-122		H
Ghanbaja J.	DEPO -P2-046	Haddou F.	SOUR -P2-019
	NANO3-O2-009	Hage M.	DEPO -P1-181
	NANO3-O4-156	Haidar D.	DEPO -P1-040
Gipperich M.	DEPO -P2-052		



Hajihoseini H.	DEPO -P1-171 PROC2-O4-169	Ibrahim S.	I
Hamza N.	NANO -P2-182	Imam A.	DEPO1-O1-023
Han L.	NANO1-K1-093	Ingason A.S.	NANO3-O4-156
Hanuš J.	NANO2-O2-105	Ingvarsson S.B.	DEPO5-O3-162
Hauet T.	NANO3-O2-009	Issaoui R.	DEPO -P1-171
Haviar S.	DEPO -P1-034		TRIB5-O1-113
Haye E.	GROM -P1-010 GROM -P2-177 NANO3-O2-009	J	
Heau C.	DEPO -P2-045 TRIB -P1-015	Jacky D.	TRIB -P2-155
Hebbar Kannur K.	TRIB -P1-015	Jacquemot A.	INDU1-O2-028
Hegemann D.	DEPO2-K1-024 GROM2-O4-012	Jama C.	DEPO -P1-181
Heikal G.	LIQU1-O3-031	Ji Q.	DEPO3-O5-140
Held J.	PROC -P2-185 PROC -P2-187	Ji M.	DEPO5-O4-037
Hemberg A.	SOUR1-O2-072	Job N.	DEPO3-O3-088
Henrion G.	LIQU1-O1-042 LIQU -P1-049 SURF -P1-051	Jousseaume V.	NANO3-O2-009
Hernandez E.	DEPO2-O2-016	Julian H.	DEPO4-O3-096
Hernandez-Rodriguez O.	SOUR -P2-107	Julin J.	PL4
Hinterer A.	TRIB4-O1-047	Jullière B.	DEPO4-K1-039
Hnilica J.	PROC1-O3-067	K	
Hoppe C.	GROM2-O3-125	Kabbara H.	TRIB1-O2-060
Horn K.	TRIB4-O1-047	Kadoc J.	NANO1-O3-095
Horwat D.	GROM1-O2-036	Kaganovich I.	TRIB -P2-155
Houška J.	DEPO -P1-034	Kagerer S.	NANO1-K1-093
Houssiau L.	NANO3-O2-009	Kahn M.	DEPO5-O2-057
Hrebik J.	INDU1-O4-138	Kaleli H.	PROC2-O5-121
Hubicka Z.	PROC2-O2-066 PROC2-O4-169	Kalendarev R.	TRIB4-O2-058
Hugon R.	DEPO -P1-145	Kasri S.	TRIB -P1-080
Huran J.	NANO2-O5-101	Kassem W.	NANO1-O5-110
		Kateb M.	DEPO -P1-040
		Katharina G.	DEPO -P1-171
		Katherine R.	PL4
		Kaushik P.	INDU -P1-136
			NANO1-O2-092



		L	
Kern F.	TRIB2-O2-013		
Khalakhan I.	NANO2-O2-105	Lacaze-Dufaure C.	GROM -P1-044
Khelissa S.	DEPO -P1-181	Lackner J.M.	TRIB4-O1-047
Khrabryi A.	NANO1-K1-093	Lacoste A.	PROC2-O3-131
Killinger A.	TRIB2-O2-013	Lagrange M.	DEPO4-O3-096
Klapetek P.	NANO1-O2-092	Laourine F.	SURF -P1-159
Klein P.	PROC1-O3-067	Latchabady S.	SOUR -P2-143
Kleinová A.	NANO2-O5-101	Latu Romain L.	TRIB3-O2-144
Kling H.	TRIB2-O3-111	Lazzaroni C.	NANO1-O3-095
Knittel S.	INDU1-O5-021	Lecas T.	DEPO5-K1-116
Kobzev A.P.	NANO2-O5-101	Leclère P.	SURF -P1-082
Kocišová E.	DEPO -P2-119	Lecocq H.	NANO2-O3-132
Koel B.	NANO1-K1-093	Lefaucheux P.	DEPO5-K1-116
Kolenatý D.	DEPO -P1-034	Lequin D.	SURF2-O1-026
Kolozsvári S.	DEPO5-O2-057 TRIB -P1-103	Leroy O.	SURF -P1-055
Konstantinidis S.	PROC2-O1-071 SOUR1-O2-072 SURF -P1-082	Leroy M-A.	SOUR -P2-064
Kopova I.	HELI1-O1-124	Leturcq R.	DEPO -P2-045
Kouicem M.	SURF -P1-146	Leutenegger D.	TRIB3-O1-129
Kovacevic L.	TRIB -P1-030	Li D.	DEPO4-O2-022
Kováčová E.	NANO2-O5-101	Lingley Z.	DEPO2-K1-024
Kozák T.	PROC2-O2-066 DEPO5-O2-057 TRIB -P1-103	Liu B.	DEPO -P1-063
Kroker M.	TRIB2-K1-065	Lombardi G.	GROM2-O2-062
Kroll L.	PROC3-O3-133	Loquai S.	NANO1-O3-095
Krstic P.	NANO1-K1-093	Loyer F.	INDU1-O5-021
Kurian B.	PROC1-O4-050 SOUR -P2-107	Lucas S.	DEPO4-O2-025
Kushner M.	PLATH00191		GROM -P1-010
Kuzminova A.	DEPO -P2-119		GROM1-O3-081
Kylián O.	DEPO -P2-119 NANO2-O2-105		GROM -P1-084
		Luik M.	GROM -P1-086
		Lundin D.	GROM -P2-177
			PROC3-O4-120
			TRIB2-O2-013
			PROC1-O1-142
			PROC2-O4-169



M			
Maekawa K.	SURF2-O1-026 SURF -P1-055	Michieli N. Michiels M. Michler J. Michlicek M.	HELI -P1-085 SOUR1-O2-072 SOUR -P2-099
Magnus F.	DEPO5-O3-162	Mickan M.	HELI1-O1-124
Maizeray A.	PROC -P2-160	Migot S.	DEPO5-K1-116
Mansour A.	NANO -P2-032	Miletic A.	NANO -P2-118
Mantel M.	TRIB3-O2-144	Mille V.	GROM1-O2-036
Marath Santhosh N.	SURF1-O2-154	Millon E.	TRIB -P1-030
Marciano J.	DEPO3-O1-102	Minea T.	NANO1-O3-095
Marcos G.	PROC -P2-160 SURF -P1-159 TRIB5-O2-141 TRIB -P2-155	Miska P.	GROM1-O1-007 NANO -P2-118
Mares P.	PROC2-O2-066	Mitronika M.	PROC1-O1-142 SOUR -P2-143 SOUR -P2-151 SOUR1-O3-153
Marotta E.	SOUR1-O1-059	Mitschker F.	DEPO -P2-046
Martel R.	SURF1-O1-070	Mobasher M.	LIQU1-O1-041
Martin J.	LIQU1-O1-042 TRIB5-O2-141	Moerman D.	SURF -P1-043 SURF -P1-150
Martínez De Bujanda J.	TRIB -P1-186	Monaghan D.	GROM2-O3-125
Martinko I.	GROM2-K1-130	Monier G.	PROCI-O4-050
Martinu L.	INDU1-O5-021	Moroni L.	SOUR -P2-107
Marty B.	SOUR -P2-064	Moscicki T.	SURF -P1-146
Matej P.	TRIB2-K1-065	Moskovkin P.	DEPO -P1-108
Mathioudaki S.	GROM -P1-084	Mücklich F.	TRIB -P2-149
Mattei G.	HELI -P1-085	Muller J.	GROM -P1-086
Mayrhofer P.H.	DEPO5-O2-057 TRIB -P1-103 TRIB -P1-103	Munteanu D.	HELI -P1-085
Mazri M.	LIQU -P1-049	Mussano F.	GROM -P2-177
Medalova J.	HELI1-O1-124	Mutel B.	DEPO1-O4-014
Meehan D.	DEPO -P2-178		HELI -P1-085
Mendizabal L.	TRIB2-O3-111		DEPO3-O5-140
Mermet F.	DEPO -P2-029		
Meyer T.	SURF -P1-148		
Meziani S.	DEPO -P2-004		
Michau D.	INDU -P1-020		



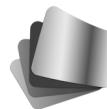
N	P
Nagy P.	SOUR -P2-099
Naja A.	DEPO -P1-145
Najah A.	PROC -P2-035 SURF -P1-051
Naudé N.	PROC2-O5-121
Nazabal V.	SURF -P1-148
Necas D.	NANO1-O2-092
Nelis T.	SOUR -P2-099
Nemec P.	SURF -P1-148
Neupert H.	DEPO1-O5-061
Ngoue D.	DEPO2-O2-016
Nguyen T.	DEPO -P1-038
Nguyen Van T.	DEPO4-O4-166
Noël C.	LIQU -P1-049 PROC -P2-035 PROC -P2-160 LIQU1-O1-042
Nominé A.	LIQU1-O1-042
Norby P.	PL1
Norrman K.	PL1
Nouveau C.	TRIB1-O2-060 TRIB -P1-068 TRIB -P2-075 TRIB -P1-080
Nozdrin M.A.	NANO2-O5-101
Ntomprougkidis V.	LIQU1-O1-042
O	
Oberberg M.	PROC3-O3-133
O'connor G.	NANO -P2-118
Orozco V.	LIQU1-O2-123
Ortiz R.	TRIB2-O3-111
Ouazene M.	LIQU -P2-175
Outeiro J.	TRIB1-O2-060
	Pace B.
	Pagano F.
	Pailoux F.
	Paint Y.
	Pajdarova A.D.
	Palacio J.F.
	Palmero A.
	Panepinto A.
	Pares V.
	Parizek M.
	Patelli A.
	Patsalas P.
	Pavlik A.
	Pentecoste-Cuynet L.
	Perraudeau A.
	Petho L.
	Petrikowski K.
	Pflug A.
	Pfuch A.
	Philippon S.
	Phillip D.
	Piani L.
	Pierson J-F.
	DEPO -P2-052
	DEPO -P2-046
	DEPO1-O3-048
	GROM1-O2-036
	DEPO -P1-145
	DEPO1-O3-048
	DEPO -P2-052
	NANO -P2-182
	GROM -P1-010
	GROM -P2-177
	NANO3-O2-009



Pleskunov P.	NANO2-O2-105	Ravisy W.	DEPO -P1-063
Polesel J.	DEPO -P1-038		DEPO3-O2-127
Poloucek P.	NANO1-O2-092		DEPO -P1-128
Poncin-Epaillard F.	DEPO -P1-011		GROM2-O2-062
	DEPO -P2-029		SURF -P1-043
	DEPO3-O3-088		
	NANO -P2-032		
Posseme N.	DEPO4-O3-096	Raynaud P.	GROM2-K1-130
Poulon-Quintin A.	INDU -P1-020	Revel A.	SOUR -P2-151
Presmanes L.	DEPO4-O5-168		SOUR1-O3-153
Price J.	SOUR -P2-107	Rice K.	INDU1-O1-190
Procházka M.	DEPO -P2-119	Richard T.	DEPO -P1-109
Profili J.	DEPO -P1-053	Richard-Plouet M.	PROC3-K1-106
	DEPO -P2-054		
	NANO2-O1-041		
	SURF -P1-043		
	SURF -P1-150		
Prosa T.J.	INDU1-O1-190		
	INDU -P1-136		
Proschwitz S.	TRIB4-O1-047	Richter A.	DEPO4-K1-039
Psiuk R.	TRIB -P2-149	Riedl H.	DEPO5-O2-057
Pupier C.	TRIB -P1-015		TRIB -P1-103
	TRIB3-O1-129		
Purans J.	NANO1-O5-110	Rigaudier T.	TRIB -P1-103
Putzschke M.	TRIB4-O1-047	Rinnert H.	SOUR -P2-064
Q		Robert U.	DEPO -P2-052
Quoizola S.	DEPO2-O2-016	Robert J.	INDU -P1-136
R		Robert Bigras G.	SOUR -P2-143
Raadu M.	PROC1-O1-142	Robert-Goumet C.	PROC -P2-087
Raitses Y.	NANO1-K1-093		SURF1-O1-070
Rajendiran S.	DEPO -P2-178	Rodríguez Trías R.J.	DEPO -P1-108
Ramoul C.	TRIB -P1-080	Rosaz G.J.	SURF -P1-146
Rassinfosse L.	GROM -P1-010	Rossall A.	TRIB -P1-186
Ratier B.	DEPO3-O4-100	Roualdès S.	DEPO1-O5-061
Ratin C.	DEPO4-O3-096	Rouessac V.	PROC3-K1-106
Rava P.	INDU1-O2-028	Rousseau A.	DEPO -P1-109
			DEPO -P2-178
			GROM -P1-044
			GROM -P1-044
			LIQU1-O3-031



Roussely G.	SOUR -P2-099	Sharaf Y.	LIQU1-O3-031
Ruch D.	TRIB4-O2-058	Shayestehaminzadeh S.	DEPO5-O3-162
S			
Sackers M.	PROC -P2-187	Shelemin A.	NANO2-O2-105
Sadek T.	TRIB4-O2-058	Shimizu T.	PROC2-O1-071
Salapare H.	GROM -P1-114	Shukurov A.	NANO2-O2-105
Santos Sousa J.	HELI1-O2-161	Sinkovits T.	DEPO -P1-109
Santra B.	NANO1-K1-093	Sinnarasa I.	DEPO4-O5-168
Sapieha J.E.	INDU1-O5-021	Sitzman S.	DEPO1-O2-025
Sapountzis A.	DEPO -P1-109	Sklias K.	HELI1-O2-161
Sarakha M.	DEPO1-O1-023	Skoric B.	TRIB -P1-030
Sarkissian A.	DEPO -P1-053 DEPO -P2-054	Slominska H.	TRIB -P2-149
Sarrette J.P.	PROC1-O5-003	Snyders R.	NANO2-O3-132 PROC1-O3-067 SOUR1-O2-072
Sasinková V.	NANO2-O5-101	Soon Chang C.	NANO3-O2-009
Sathanikan A.	GROM -P1-114	Sortais P.	SOUR -P2-099
Satriano C.	NANO2-O3-132	Soucek P.	PROC1-O3-067 TRIB2-K1-065
Sauvage T.	DEPO1-O1-023 DEPO5-K1-116	Soum-Glaude A.	DEPO2-O2-016
Sauzet H.	DEPO -P2-045	Stafford L.	DEPO -P1-053 DEPO -P2-054
Schuengel E.	DEPO2-O3-078		NANO2-O1-041 PROC -P2-056
Schulze J.	PROC3-O3-133 PROC3-O2-135		PROC -P2-087 PROC2-O5-121 SURF -P1-043
Schulz-Von Der Gathen V.	PROC -P2-185		SURF1-O1-070
Schüngel E.	PROC -P2-134 PROC3-O2-135		SURF -P1-150 TRIB4-O2-058
Schwan A.M.	TRIB4-O1-047	Stamate E.	PL1
Schwyn Thöny S.	DEPO2-O3-078 PROC -P2-134	Stanley M.	DEPO3-O1-102
Scopece P.	HELI -P1-085 SOUR1-O1-059	Stewig C.	PL4
Selegard L.	TRIB2-O3-111	Stögmüller P.	TRIB4-O1-047
Selinsky R.	NANO1-K1-093	Stolz A.	NANO -P2-118
Semmar N.	NANO -P2-118	Sublet A.	DEPO1-O5-061 PROC3-K1-106
Sgrilli T.	SOUR -P2-107	Suciuc V.	DEPO1-O4-014



T	U	V	W
Tabbal M.	DEPO -P1-040 NANO -P2-118	Tumanov N.	GROM -P1-010
Taborelli M.	DEPO1-O5-061 DEPO -P1-109 PROC3-K1-106	Urbanietz T.	PL4
Tahara S.	SURF2-O1-026 SURF -P1-055	Vachey C.	TRIB3-O2-144
Tailhades P.	DEPO4-O5-168	Vaidulych M.	NANO2-O2-105
Talbi A.	NANO -P2-118	Vandenabeele C.	GROM -P1-084
Tallaire A.	NANO1-O3-095	Van-Straaten M.	DEPO4-O3-096
Tampieri F.	SOUR1-O1-059	Varenne C.	DEPO -P1-108
Tavernier A.	DEPO4-O3-096	Vasiliu A.	INDU -P1-188
Terek P.	TRIB -P1-030	Vašina P.	TRIB2-K1-065 PROC1-O3-067
Teulé-Gay L.	INDU -P1-020	Vass M.	PROC3-O2-135
Thiemann-Monjé S.	PROC -P2-187	Vaz F.	DEPO1-O4-014
Thimont Y.	DEPO4-O5-168	Vedraine S.	DEPO3-O4-100
Thiry D.	NANO2-O3-132	Veillerot M.	DEPO4-O3-096
Thomann A.L.	DEPO5-K1-116 GROM1-O1-007 NANO -P2-118	Vincent J.	TRIB5-O2-141
Thomann A-L.	SURF -P1-082	Vincent B.	SOUR1-O3-153
Thomas L.	DEPO2-O2-016	Vinchon P.	SURF1-O1-070
Thorsteinsson E.B.	DEPO5-O3-162	Vinx N.	NANO2-O3-132
Tillocher T.	SURF2-O1-026 SURF -P1-055	Vlcek J.	DEPO -P1-034
Tissandier L.	SOUR -P2-064	Von Keudell A.	PL4
Tlili B.	TRIB -P1-068	Vulliet J.	PROC -P2-185 PROC -P2-187
Tomasella E.	DEPO1-O1-023 DEPO -P1-108 SURF -P1-146	Vystavel T.	DEPO5-K1-116
Trahan J.	SURF -P1-150	Wagenaars E.	DEPO -P2-178
Tran T.H.	DEPO -P1-011	Waldhauser W.	TRIB4-O1-047
Trava-Airoldi V.J.	TRIB1-O1-005	Wang X.	DEPO5-O4-037
Trigui A.	TRIB -P2-155	Werner F.	DEPO4-O2-022
Tristant P.	DEPO3-O4-100	Wojcik T.	DEPO5-O2-057 TRIB -P1-103
Tsikata S.	SOUR1-O3-153		

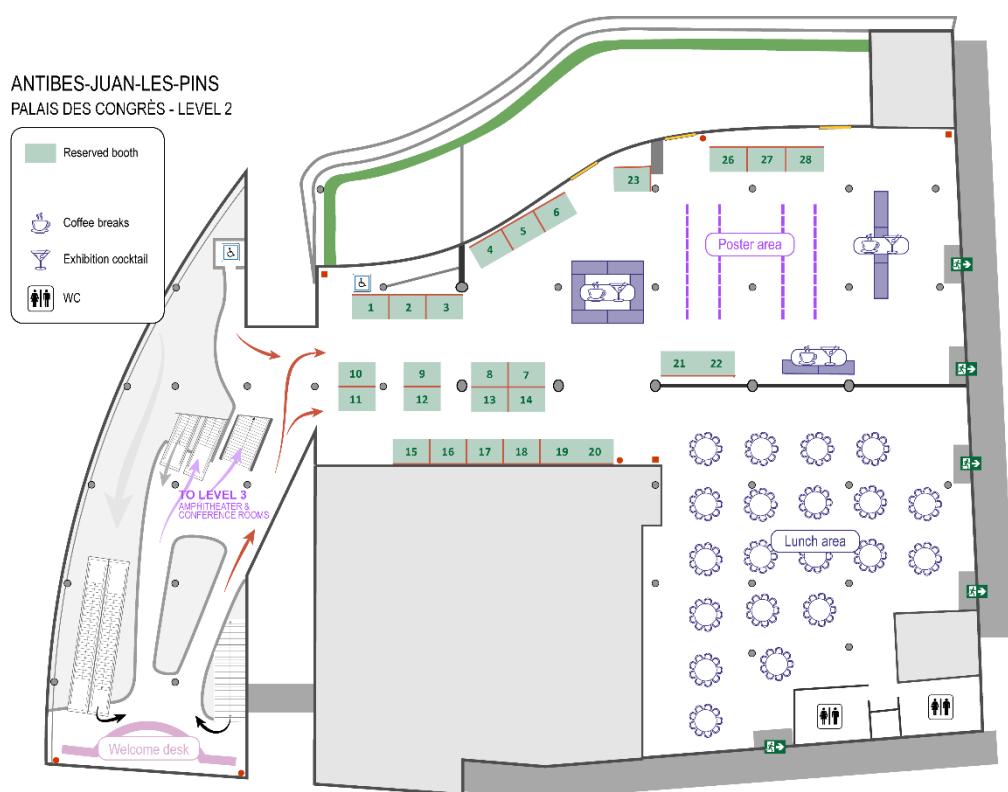


Y	Z
Yaddaden C.	DEPO -P1-074
Yagi H.	GROM -P1-098
Yamazaki K.	SURF2-O1-026 SURF -P1-055
Yang M.	PROC2-O1-071
Yang Z.	DEPO5-O4-037
Yang R.	PROC2-O3-131
Yatom S.	NANO1-K1-093
Yatsuda K.	SURF2-O1-026 SURF -P1-055
Yeh Y.W.	NANO1-K1-093
Yimeng C.	INDU -P1-136
Yin Vallgren C.	DEPO1-O5-061
Yudate S.	GROM -P1-098
	Zabransky L.
	Zajickova L.
	Zaniol B.
	Zauner L.
	Zeman P.
	Zenerino A.
	Zerguini T.H.
	Zgheib J.
	Zhang Y.
	Zubkins M.
	TRIB2-K1-065
	HELI1-O1-124
	NANO1-O2-092
	SOUR1-O1-059
	DEPO5-O2-057
	TRIB -P1-103
	TRIB -P1-103
	DEPO5-O2-057
	GROM -P1-114
	LIQU -P2-176
	PROC -P2-139
	TRIB1-O2-060
	NANO1-O5-110



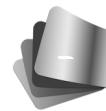
EXHIBITORS

Exhibition map



List of exhibitors

Company	booth	Company	booth
AGC PLASMA TECH SOLUTIONS	18	KURT J. LESKER	01
ALLIANCE CONCEPT	09	MICROTEST	04
AMPERE INDUSTRIE	14	NEYCO	11
BRONKHORST	03	PFEIFFER VACUUM	12
BUSCH	26	PHYSICAL INSTRUMENTS	28
CAMECA	08	POLYGON PHYSICS	07
ELETTRORAVA	04	ROBEKO	21-22
FRANCE SCIENTIFIQUE	13	SAIREM	19-20
HIDEN ANALYTICAL	13	SCIA SYSTEMS	16
HORIBA	23	SCIENTEC	17
IMPEDANS	05	SEMILAB	27
INFICON	06	TECHNIX	02
J. SCHNEIDER ELEKTROTECHNIK	10	VAT	15



AGC PLASMA TECHNOLOGY SOLUTIONS

Stand #18

AGC Plasma Technology Solutions brings the coating technologies used within the glass industry available to a broad range of industries. Our fields of expertise include magnetron sputtering, plasma enhanced chemical vapor deposition (PE CVD) and ion beam implantation. The value proposal of AGC Plasma technology Solutions is that we are an industrial partner to upscale innovative plasma coating processes and have the capabilities to support our customers till reaching operational excellence in their production.

AGC Plasma has a customer centric approach with a demonstration center with pilot coating lines and extensive analysis tools in Lauenförde, Germany at

the service of our customers to make product prototypes and realize proof of concepts.

Next, AGC Plasma is a one-stop provider for the vacuum plasma equipment. We take full responsibility for the project management and start-up of a turnkey vacuum plasma process line including integrated process control.



Plasma
Technology
Solutions

Voorstraat 27
2400 Mol
Belgium
+32 499 99 30 09
jeroen.schotsaert@eu.agc.com
www.agc-plasma.com

ALLIANCE CONCEPT

Stand # 09

Alliance Concept is an internationally renowned French manufacturer of high-end thin film deposition equipment by evaporation and magnetron sputtering. Alliance Concept also supplies turnkey helium and hydrogen tracer gas control machines as well as any other system requiring the implementation of vacuum technologies, such as ultra-vacuum degassing or surface activation by cold plasma.

Catalog or customized machines, Alliance Concept addresses its systems to scientific research laboratories but also to industrialists from all sectors: from the automotive industry to aeronautics, including semiconductors, photovoltaics, energy, medical, watchmaking and defense...

With 28 years experience validated by hundreds of equipment in service, Alliance Concept knows how to innovate

to satisfy the most demanding requests of its customers.

Thanks to the machine park of its R & D laboratory, Alliance Concept offers its customers its knowledge to assist them in the development of innovative thin film deposition and leak testing processes.

Alliance Concept is committed to providing a complete service, including technical and commercial needs, design, implementation and monitoring of equipment, all based on a rigorous ISO9001 certified management strategy.



allianceconcept

4 avenue du Pont de Tasset
74960 Cran Gevrier

France

+33 (0)4 50 57 93 85

contact@alliance-concept.com

www.alliance-concept.com



A.M.P.E.R.E. INDUSTRIE

Stand # 14

A.M.P.E.R.E. is a European based family owned company established in 1967 and specialised in the field of non-ferrous metals and surface treatment. For more than twelve years we have been serving the market of PVD, in Europe and worldwide.

We deliver a full range of products for industrial production, industrial pilot as well as Research & Development. Our sputtering targets, arc cathodes and evaporation materials are used for the deposition of wear, tribological, decorative, architectural and automotive glass, photovoltaic, precision optic,

ophthalmic and medical coatings. We also provide ceramics and refractory metals used inside the machines, filaments, liners and boats for evaporation systems.

Dedicated to our clients, we work accordingly to their specifications in order to offer tailor-made solutions.



7 rue Pierre Devaux
69360 Sérézin-du-Rhône
France
+33 478 023 370
pvd@ampere.com
www.ampere.com

BRONKHORST

Stand # 03

Bronkhorst offers an extensive range of thermal mass, Coriolis and ultrasonic flow meters and controllers. Its flow instruments are used in various processing methods: thermal, plasma, chemical, spray, ALD, CVD, RTP (annealed), etc., to process electronic components, glass, metal or to facilitate the fixing of inks when printing on plastic films. The devices are also used for gas mixing plates, thin-film application or inerting.

BRONKHORST France, located in Montigny les Cormeilles (95), has a service department and calibration facilities, so it is able to provide support and all after-sales service operations.

Bronkhorst France presents the following instruments and systems:

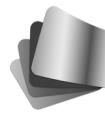
- Thermal mass flowmeters / controllers for gases and liquids
- Coriolis flowmeters and controllers
- Micro-flow dosing system with pump or control valve

- Ultrasonic flowmeters for low flows of liquids
- Pressure transmitters and controllers
- On-site calibration, technical service, start-up assistance
- Metrology, ISO 17025 certification for gas, liquid and pressure (on actual gas as an option),
- Evaporation systems, humidification systems, vapor generation systems
- Gas and liquid counters
- Fluidic systems, skids, test benches, gas mixers



Bronkhorst®
FRANCE

53 rue Jacques Verniol
95370 Montigny les Cormeilles
France
+33 (0)1 34 50 87 00
sales@bronkhorst.fr
www.bronkhorst.fr



BUSCH

Stand # 26

With more than 50 years of experience and expertise in the manufacture of vacuum systems, Busch offers a very wide selection of vacuum pumps but also customized solutions for all types of applications. The various dry vacuum pump technologies developed by Busch ensure a contamination-free process. Whatever your plasma application, Busch has the solution to meet your expectations without any compromise.

Fossa spiral pumps are hermetically sealed with completely dry compression. The high degree of compression ensures maximum suction capacity with minimal energy consumption.

COBRA Semicon dry screw pumps offer state-of-the-art solutions for the most demanding processes. Equipped with high-performance motors and an optimized monitoring function, COBRA

Semicon pumps offer a high potential for energy savings

Busch VacTest offers an innovative and comprehensive portfolio of active vacuum gauges and controllers that combine the latest advances in vacuum metrology with exceptional manufacturing quality. Wherever you are in the world, Busch Service is at your side for your consulting, commissioning, maintenance, overhaul or training needs.



Pompes à Vide et Systèmes

16 rue du Bois Chaland
91090 Lisses
France
+ 33 (0)1 69 89 89 89
busch@busch.fr
www.busch.fr

CAMECA

Stand # 08

CAMECA is a world premier supplier of high-performance analytical instrumentation for R&D and process control of novel materials and advanced semiconductors. Our instruments measure elemental and isotopic composition down atomic resolution and equip the most prestigious government and university labs as well as leading high-tech industrial companies, supporting breakthrough research in materials and nanotechnologies, nuclear sciences, cell biology, environmental studies, and more. Our mission is to offer our customers the highest analytical performance in their specialized characterization fields.

The LEAP® 5000 Atom Probe Tomograph (APT) is the state-of-the-art instrument for 3d compositional analysis at near atomic resolution. Applications include the compositional characterization of interfaces, grain boundaries, defects and dislocations,

the detection of clusters and the study of precipitation-formation reactions.

The IMS 7f-Auto, NanoSIMS 50L and IMS Wf Secondary Ion Mass Spectrometers (SIMS) lead the world for semiconductor, PV and LED characterization thanks to unparalleled performance in depth profile monitoring (implants), trace element detection (contamination) and diffusion/segregation in-situ characterization.

The SXFive-TACTIS Electron Probe Microanalyzer (EPMA) delivers high spatial resolution x-ray mapping and quantitative analysis in metals and alloys.



SCIENCE & METROLOGY SOLUTIONS

29 quai des Grésillons
92622 Gennevilliers Cedex
France
cameca.info@ametek.com
www.cameca.com



HIDEN ANALYTICAL

Stand # 13

Hiden Analytical celebrates 35 years of design, development and manufacture of quadrupole mass spectrometers. Hiden Analytical is represented in France by the company France Scientifique, distributor of scientific equipment, including in the product range:

- Elemental analysis: XRF, LIBS, micro-XRF, TXRF, OES, CS/ONH and mass spectrometer
- Metallographic sample preparation and milling
- Microscopy: desktop SEM, AFM, digital microscope
- Mechanical testing: tensile / compression, Rockwell / Brinell / Vickers hardness, salt spray chambers
- Chemistry of surfaces: measurement of contact angle, tensiometer

Regarding mass spectrometers, our products address a diverse range of applications - precision gas analysis,

plasma diagnostics by direct measurement of plasma ions and ion energies, SIMS probes for UHV surface science, catalysis performance quantification, thermo-gravimetric studies - over a pressure range extending from 30 bar processes down to UHV/XHV.

With sales and service centres situated across the globe, Hiden Analytical is committed to providing a fast, friendly and professional response, through our teams of application specialists, wherever our customers are located.



420 Europa Boulevard
Warrington WA5 7UN
United Kingdom
+33 (0)6 11 81 22 87
t.gaudy@hiden.fr
www.hidenanalytical.com

HORIBA

Stand # 23

HORIBA is a global leader providing an extensive range of measurement and analysis instruments for various applications in automotive R&D, process and environmental monitoring, in-vitro medical diagnostics, semiconductor and thin film manufacturing. Many of HORIBA's solutions are underpinned by our expertise in Scientific research and quality control measurements.

With over two centuries of experience in Spectroscopy and 45 years in gas flow control, HORIBA is one of only a few OEM companies in the world who can provide solutions for measurement, control and

analysis that are utilised to help ensure process reliability, repeatability and reproducibility in the low-pressure plasma environments. HORIBA's material characterisation solutions enables stabilisation and confidence in recipe composition, coating thickness and uniformity.



Kyoto Close, Moulton Park
Northampton NN3 6FL
United Kingdom
+44 (0)1604 542 600
vacuum-coating.huk@horiba.com
<https://horiba-vacuumcoating.com/>



IMPEDANS

Stand # 05

Impedans provide you with intelligent sensing platforms for radio-frequency (RF) and plasma process monitoring. Our products find applications in fundamental research, process development, tool design, process control and fault detection and classification (FDC). We serve a wide range of industries, due to the ubiquitous nature of RF and plasma processing, such as semiconductor, vacuum coating, medical device, hard disk and aerospace among many others.

Our value proposition is that we provide you with an independent diagnosis of your process health, using intelligent, internet-

enabled sensing platforms, in conjunction with our vast experience in RF and plasma systems, to help you solve the most complex processing issues.



Chase House City Junction Business Park
D17 AK63 Dublin
Ireland
+353 1 8428826
business@impedans.com
www.impedans.com

INFICON

Stand # 06

INFICON is a leading provider of innovative instrumentation, critical sensor technologies, and advanced process control software that enhance productivity and quality in sophisticated industrial vacuum processes. These analysis, measurement and control products are essential for gas leak detection in air conditioning/refrigeration, and automotive manufacturing. They are vital to equipment manufacturers and end-users in the complex fabrication of semiconductors and thin film coatings for optics, flat panel displays, solar cells and industrial vacuum coating applications. Other users of vacuum based processes include the life sciences, research, aerospace, packaging, heat treatment, laser cutting and many other industrial processes. We also leverage our expertise in vacuum technology to provide

unique, toxic chemical analysis products for emergency response, security, and environmental monitoring. INFICON is headquartered in Switzerland and has world-class manufacturing facilities in Europe, the United States and China, as well as subsidiaries in China, Denmark, Finland, France, Germany, India, Italy, Japan, Korea, Liechtenstein, Singapore, Sweden, Switzerland, Taiwan, the United Kingdom and the United States. INFICON registered shares (IFCN) are listed on SIX Swiss Exchange.



Bonner Str. 498
50968 Cologne
Germany
+49 221 56788 100
sales.europe@inficon.com
www.inficon.com



J. SCHNEIDER ELEKTROTECHNIK

Stand # 10

Since more than 80 years J. Schneider Elektrotechnik delivers customer-specified and standard power supplies all over the world. 360 employees are working in the divisions "Transformers", "Service Center Electrical Drives" and "High Voltage Power Supplies/UPS".

In the high voltage power supply-division J. Schneider especially designs and manufactures power supplies for the high voltage and vacuum process equipment in the output power range 1kW-120kW with output voltages 400V-170kV. The high voltage power supplies for ion and electron beam applications, x-ray, laser and high voltage plasma processes work with high reliability and robustness in several applications such as e-beam evaporation, e-beam welding, ion beam systems, capacitor charge systems, glow discharge, x-ray supplies and sputter applications.

The products of the PLASMATEC series are especially designed for vacuum coating processes. They are available in a wide output power range from 3 kW up to 20 kW and due to their modularity they can be connected in parallel to increase the output power up to 200 kW. The PLASMATEC series is characterized by the most sophisticated, flexible and adjustable arc management with extremely low passive output energy and a high output power density.



**J. Schneider
Elektrotechnik**

Helmholtzstraße 13
77652 Offenburg
Germany
+49/(0)781/206-217
m.schweiger@j-schneider.de
www.j-schneider.de

KURT J. LESKER

Stand # 01

Kurt J. Lesker is a leading global provider of high-quality vacuum hardware, deposition systems and custom chambers, with the goal of enabling the innovation, creation and advancement of a vast array of vacuum technology. The breadth of markets we serve include LEDs, Optics, UHV/Synchrotrons, Electronics, Wear & Decorative Coatings and R&D.

We are committed to helping our customers compete and succeed on the leading edge of technology. From custom vacuum chambers produced at our European based manufacturing facility to

market leading thin film deposition systems built in-house, accompanied by fast and reliable technical service and support, Kurt J. Lesker has positioned itself successfully as a global leader and expert in 'all things vacuum'.

Kurt J. Lesker
Company

15/16 Burgess Road
East Sussex
TN35 4 NR Hastings
United Kingdom
+44 1424 458100
emeiasales@lesker.com
www.lesker.com



MICROTEST

Stand # 04

MICROTEST: Equipment & consumables

Technical expertise – After-sales Service – Maintenance – Consumables

Our wide offer and technical knowledge support the implementation of your projects, with our team at your side to provide assistance and expert follow up. Our equipment:

- Thin film coating: with our partner Elettorava SPA, we are experts in designing, production, research and development of thin films deposition systems involving DC/RF sputtering, PECVD, HFCVD, E-Beam deposition techniques. One of the major activities includes design and development of PECVD single chamber and cluster chamber deposition systems. A wide range of processes has been implemented in the Process Chambers, including rf-PECVD, vhf-PECVD, ECR-PECVD and HWCVD

- Pumps and Industrial balancing machines
- Spin/spray Coaters/developers, Wafer bonders, Hotplates, Wet process for R&D and production
- High Temperature Ovens
- Atmospheric Plasma Cleaner
- Mask aligners, laser Lithography
- Second Source Spare parts (Novellus – Applied – LAM...)
- Consumables & Tools: Tweezers - Vacuum handlers, frames and shippers...



Equipment & Consumables for the semiconductors and hybrids

ZA La Garrigue du Rameyron

84830 Sérignan

France

+33 (0)4 90 40 60 90

microtest@microtest-semi.com

www.microtest-semi.com

NEYCO

Stand # 11

Over the past 60 years, Neyco has consolidated its position as the specialist in the fields of high vacuum, inorganic materials and thin films

Our main skills, capabilities and knowledge include:

- Materials: inorganic powders and pellets, sputtering targets & backing plates, precious metals, filaments & boats, liners, wafers & substrates
- Thin films components: electron guns and ion guns spare parts, thickness measurement and quartz, magnetrons, electron guns,
- Vacuum components: pressure measurement, KF/ISO/CF vacuum fittings, glass & quartz components, viewports, feedthroughs, valves

- Electron Microscopy: consumables dedicated to SEM & TEM

Our company is ISO 9001 and ISO 14001 certified. This ensures that you receive a guaranteed quality of service with the lowest environmental impact.



Vacuum & Materials

30 avenue de la Paix

92170 Vanves

France

+33 (0)1 41 90 50 50

contact@neyco.fr

www.neyco.fr



PFEIFFER VACUUM

Stand # 12

Pfeiffer Vacuum – a name that stands for innovative vacuum and leak detection solutions, high technology and dependable products, along with first-class service.

Pfeiffer Vacuum is at the origin of the invention of many products in the vacuum field.

Its components and equipment are used to generate a clean and dry vacuum, to test the tightness of industrial installations and equipment, to measure level of vacuum and to carry out gas analyses in the fields of research and industrial process.

Pfeiffer Vacuum provides itself with the means to provide each customer with an optimal and adapted vacuum solution. The group tends to maintain its Research and Development momentum. This is in order to maintain excellence and be an industrial reference based on high-tech products. The main products are developed in our R&D

(Asslar and Annecy) and are subjected to numerous tests before being marketed.

In order to best meet customer demand, Pfeiffer Vacuum ensures that its commitments in terms of sustainable development, quality and safety are met. The group is proud to highlight its two certifications: ISO 9001 (quality management) and 14001 (environmental management). Thanks to its desire to provide increasingly eco-responsible products, eco-design has been introduced into the production process.

PFEIFFER  **VACUUM**

98 avenue de Brogny
BP 2069
74009 Annecy Cedex
France
+33 (0)4 50 65 70 37
info@pfeiffer-vacuum.fr
www.pfeiffer-vacuum.com

PHYSICAL INSTRUMENTS

Stand # 28

Founded in 2005 PHYSICAL Instruments is a sales agency distributing over the French market High Voltage DC Power Supplies and Pulsed High Voltage Generators, DC to DC HV converters. Also we offer a nice portfolio of HV cables and connectors.

We are collaborating with expert engineers, physicists, production and quality specialists, thus offering excellent products.

The complete development and production process is done in Germany. Customers are able to obtain complete fine-tuned solutions for supplying

industrial experiments from a single source.

All units are available as standard version or optionally with digital interfaces. Therefore integration into computer based systems is guaranteed...

Physical
instruments

82 impasse de la Grande Chantourne
38330 St Nazaires Les Eymes
France
+33 (0)9 50 13 94 03
ludovic.ruse@physical-instruments.fr
www.physical-instruments.fr



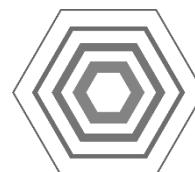
POLYGON PHYSICS

Stand # 07

Polygon Physics designs and produces charged particle or plasma sources as well as complete systems for vacuum surface engineering applications such as ion beam sputter deposition (including combinatorial thin film deposition), surface nano-structuring, ion beam figuring, electron beam welding, and ion implantation.

We are specialized in ultra-compact ultra-low power ECR technology. This technology enables stable and reliable plasma, ion or electron beams and beam arrays of any size and shape. Due to the filament-less design of our products also reactive gases (e.g. oxygen) can be used, and the maintenance is very low. We can offer from a very cost-effective version to very specific versions matched to the power requirement of the user.

In need of a linear, rectangular or circular beam for a particular surface treatment? We have a unique expertise in creating the beam of your choice, small or large, high brightness or high current.



**POLYGON
PHYSICS**

53 rue des Martyrs
38026 Grenoble Cedex
France
+33 (0)4 76 28 40 49
info@polygonphysics.com
www.polygonphysics.com

robeko

Stand # 21-22

robeko is a leading technology company, providing technical consulting and sales of components and materials for PVD- and PECVD -processes.

The company has an own application center with several industrial scale sputtering systems and a target production including target bond shop as well as a sales portfolio of high end, complementary components for thin film production, plasma analysis and plasma surface treatment. We are proud to be the sales agent for leading manufactures like Sputtering Components, Thin Film Consulting, PLASUS, Impedans, Sairem, ionics and Magpuls. Accompanied by the in house developed high power

microwave source MIRO robeko is able to provide a full range of products in the field of thin film technology.

Continuous production process development and training of our employees assure deep understanding and expertise of the products and their applications. This allows robeko to consult with the customers and advice the best solution for their needs.



An der Heide 3 B
67678 Mehlingen
Germany
+49 6303 999 67-00
info@robeko.de
www.robeko.de



SAIREM

Stand # 19-20

SAIREM is the Microwave and Radio Frequency specialist with applications in industry, food processing, global science, chemistry, plasma, and medicine. The equipment, designed and developed by SAIREM, can operate at power levels of a few watts up to several hundreds of kilowatts at all standard ISM frequencies. The company offers a wide range of solutions, including innovating generators, components for energy transfer, plasma sources, or turnkey solutions, and all the associated technologies to optimize your application: reactor design, protection and radiation control, tuning and automation systems...In the plasma activity, SAIREM designs, manufactures and provides microwave plasma sources and associated generators in the whole pressure and power range. From solutions for large treatment areas in the Pa range using solid state generators and autotuned plasma sources to atmospheric plasma torch working at several kW.

Recent developments in plasma

- ECR coaxial plasma source Aura-Wave (SVTM innovation award 2015)
- Medium pressure coaxial plasma source Hi-Wave (SVTM innovation award 2015)
- Surface wave launcher S-Wave (SVTM innovation award 2018)
- New industrial 6 kW atmospheric downstream plasma source with ignition system
- Solid state microwave generator 2.45 GHz – 1000 W



82 rue Elisée Reclus
69150 Décines-Charpieu
France
+33 (0)4 72 01 81 60
commercial@sairem.com
www.sairem.com

scia SYSTEMS

Stand # 16

scia Systems GmbH is a full range supplier of precise surface processing equipment, based on advanced ion beam and plasma technologies. The systems are applicable for coating and etching processes in the production of microelectronics, MEMS and precision optical components, in both, high volume production as well as research and development environments.

Due to their flexible and modular design, the systems can be configured according to customer specific requirements. Amongst others by combining several vacuum process chambers into cluster or in-line solutions. Together with our worldwide service partners, we offer comprehensive service and superior technology support.

Technology Portfolio

- Ion Beam Trimming (IBT)
- Ion Beam Etching and Milling (IBE/IBM)
- Dual Ion Beam Sputtering (DIBS)
- Plasma Enhanced Chemical Vapor Deposition (PECVD)
- Reactive Ion Etching (RIE)
- Magnetron Sputtering
- Dry Cleaning



scia Systems GmbH
Annaberger Str. 240
09125 Chemnitz
Germany
+49 371 5347 780
info@scia-systems.com
www.scia-systems.com



SCIENTEC

Stand # 17

ScienTec is one of the largest French distributors in the field of surface analysis from nanometer to millimeter, for research & industry.

ScienTec is the representative of Prevac that manufacture Vacuum systems for analysis & deposition (PVD – PLD – MBE)

ScienTec also offers a wide range of scientific equipments:

- Nanoindentors: Hardness, scratch, Young modulus, ambient/vacuum environments
- Optical and mechanical profilometers: single & automated measurements
- Thin film analyzers: Single-spot, microscopic-spot thickness or automated
- Vacuum systems for analysis & deposition (PVD – PLD – MBE)

- SEM microscopes: Superior price-to-performance tabletop and standard SEM (robustness, ease-of-use, EDS analysis)
- AFM microscopes: Best price / performance AFM (High resolution, ResiScope, HD-KFM, sMIM, multiple environments)
- IR and RAMAN spectroscopies: submicron scale, better than ATR



17 avenue des Andes
Bâtiment le Cèdre
91940 Les Ulis
France
info@scientec.fr
www.scientec.fr

SEMILAB

Stand # 27

SEMILAB is a major supplier of advanced metrology equipment and techniques, for the control of processes and materials in the field of Semiconductor, III-V, LED Photovoltaic and printed electronics, both for research and development and production control.

Our techniques and measuring instruments provide mechanical, opticals and electricals characterizations for a wide range of bulk materials and thin layers, whose structures can be simple or multilayered. Our equipments can be implemented fully manual and R&D type but also online for production control or even integrated in situ within process equipment.

SEMILAB has a wide variety of measurement techniques, many of which are contactless and non-destructive such as ellipsometry and spectroscopic reflectometry, photoluminescence, which

allow complete control of all the optical properties of the materials.

SEMILAB proposes also a very wide range of techniques for characterizing electrical properties of thin metallics, semiconductors and transparent conductive layers, such as resistance, dopant, mobility by hall effect, contamination, life time, and diffusion length...

And since recently SEMILAB has included in his product portfolio mechanical tests by AFM, SPM and Nanoindentation.



Prielle Kornelia u. 2
1117 Budapest
Hungary
+33 (0)6 84 78 79 17
christophe.defranoux@semilab.com
www.semilab.hu



TECHNIX

Stand # 02

Since 2000, Technix designs and manufactures in France a wide range of high voltage DC power supplies based on the zero current switching (ZCS) resonance technology. The range spans from 1 kV to over 100 kV and from 300 W to over 100 kW.

We offer a flexible modular design and customized solutions, while keeping high reliability and fast delivery time through a wide range of options.

Technix generators are used all around the world within many important industrial groups and famous research laboratories for applications like HiPIMS solutions, low pressure microwave discharges, Atmospheric plasmas, DC discharges,

physical vapor deposition (PVD) ,Electron beam evaporation, DC Power Magnetron Sputtering, Dielectric Barrier Discharge (DBD), Molecular beam epitaxy (MBE), etc.



6/8 rue Eugène Dupuis
ZAC Europarc
94000 Créteil
France
+33 (0)1 56 71 28 60
contact@technix-hv.com
www.technix-hv.com

VAT

Stand # 15

VAT is the leading global developer, manufacturer and supplier of high-end vacuum valves. VAT vacuum valves are mission-critical components for advanced manufacturing processes of innovative products used in daily life like such as portable devices, flat screen monitors or solar panels. VAT is organized into three different reporting segments: Valves, Global Services and Industry offering high-end vacuum valves, multi-valve modules, edge-welded bellows and related value-added services for an array

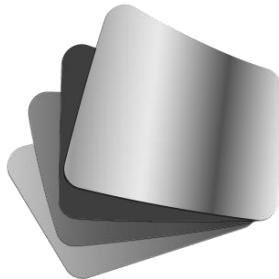
of vacuum applications. VAT Group is a global player with main manufacturing sites in Haag (Switzerland), Penang (Malaysia) and Arad (Romania).



26 avenue Jean Kuntzmann
38330 Monbonnot Saint Martin
France
+33 4 85 88 00 72
fr@vatvalve.com
www.vatvalve.com



See you for the 2nd edition



PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

13 - 17 September 2021
Antibes, French Riviera

www.plathinium.com

The HORIBA Group, made up of 49 companies in 28 countries, is a world leading Technology company that provides precision analytical and measurement systems. HORIBA's products and engineering solutions bring together 45 years of expertise in fluid control and over two centuries of experience in spectroscopy to provide vacuum coating OEMs and end users with a unique value proposition.

HORIBA's Applications and Technology experts work as part of your team to ensure OEMs and end users receive the best possible support to increase yield, minimize waste and maximise productivity when using our repeatable, reliable and reproducible solutions.

When it comes to confidence in delivering fluids and monitoring the quality of low-pressure plasma environments; HORIBA has it covered. HORIBA is recognised globally in the Semiconductor industry as a leading provider of solutions that contribute to process stability and consistent control for etching and deposition processes.

With a wide range of Instrumentation, controllers, monitors, analysers, and bespoke engineering solutions, HORIBA is a proven single source for consistent quality assurance, process control and monitoring both for in-situ / in-line and offline applications.

RGA Redefined

HORIBA's compact process Gas Monitor Micropole system is one of the smallest complete mass spectrometer systems in the world. Delivering high performance and offering high pressure operation combined with ease of use, rapid installation and intuitive feature-rich software this product provides users with a proven no-nonsense solution to complex gas analysis.

For more information

Call: +44 (0)1604 542 600

Email: vacuum-coating.huk@horiba.com

Visit: <https://horiba-vacuumcoating.com>



Overview program



PLATHINIUM
PLASMA THIN FILM INTERNATIONAL UNION MEETING

CONFERENCE SECRETARY: FRENCH VACUUM SOCIETY

Société Française du Vide (SFV) - 19 rue du Renard F-75004 Paris - phone: +33 (0)1 53 01 90 30 - sfv@vide.org - www.vide.org